

(FILE 'HOME' ENTERED AT 16:40:39 ON 22 JUL 2002)

FILE 'REGISTRY' ENTERED AT 16:40:47 ON 22 JUL 2002

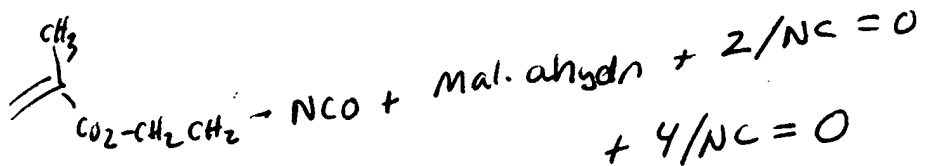
L1 0 S 30674-66-1/RN
L2 0 S 30674-66-1/CRN
L3 1476 S 30674-80-7/CRN *^CO2-ET-NCO*
L4 1 S 30674-80-7/RN
L5 0 S ACRYLOXYL ETHYL ISOCYANATE
L6 2 S ACRYLOXYETHYL ISOCYANATE

FILE 'CAPLUS' ENTERED AT 16:43:18 ON 22 JUL 2002

L7 2 S L6

FILE 'REGISTRY' ENTERED AT 16:43:40 ON 22 JUL 2002

L8 21269 S 108-31-6/CRN *✓ mal. an*
L9 20 S L8 AND L3 *✓*
L10 0 S L9 AND 2/NC
L11 66638 S 80-62-6/CRN OR 96-33-3/CRN - *MAH or M mat*
L12 9 S L9 AND L11 *✓*
L13 0 S L12 AND 3/NC *✓*
L14 0 S L12 AND 4/NC *✓*



was formed into a film from an 18% DMF soln. to give a sample which absorbed Acilan Direct Blue A and Astrazon Blue B at 0.27 and 0.53 g dye/100 g film compared to 0.23 and 0.05 g dye for a film prepd. from Me acrylate instead of II.

IT 34977-10-1P

RL: PREP (Preparation)
(prepn. of)

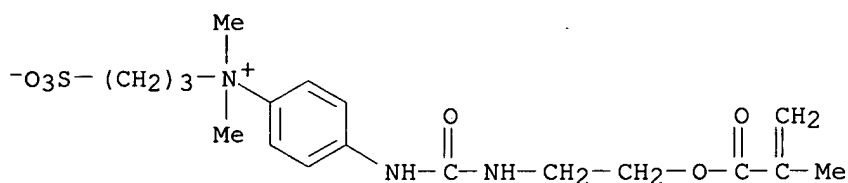
RN 34977-10-1 CAPLUS

CN Benzenaminium, N,N-dimethyl-4-[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]carbonyl]amino]-N-(3-sulfopropyl)-, inner salt, polymer with 2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 5205-97-0

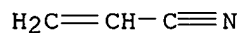
CMF C18 H27 N3 O6 S



CM 2

CRN 107-13-1

CMF C3 H3 N



L13 ANSWER 69 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1969:29972 CAPLUS

DN 70:29972

TI Acrylonitrile copolymers containing sulfonic groups

IN Szita, Jenő; Bahr, Ulrich; Marzolph, Herbert; Nischk, Gunther

PA Farbenfabriken Bayer A.-G.

SO Brit., 10 pp.

CODEN: BRXXAA

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	GB 1132665		19681106		
PRAI	DE		19660728		

AB Polyacrylonitrile fibers are given improved dye retention and thermal stability by incorporating into the polymer a small amt. of an ethylenically unsatd. compd. $\text{CH}_2:\text{CMeCO}_2\text{CH}_2\text{CH}_2\text{NHCONHR}$ (I). Thus, 3.5 kg. of a mixt. of acrylonitrile and Me acrylate (II) (.apprx.19:1) was added at 55.degree. under N to 45 l. deionized water (adjusted to pH 3.5 with $\text{N H}_2\text{SO}_4$), followed by successive addn. of 23.0 g. $\text{K}_2\text{S}_2\text{O}_8$, 102.0 g. $\text{Na}_2\text{S}_2\text{O}_5$, and .apprx.0.17 kg. I ($\text{R} = \text{p-NaO}_3\text{SC}_6\text{H}_4$), each dissolved in 500 ml. H_2O . The temp. was kept at 55.degree. for 4 hrs. and the fine-grained polymer was isolated and dried in vacuo at 60.degree.. The extinction coeff. at 470 m.mu. for this polymer after 20 hrs. at 88.degree. (as a 5% HCONMe_2

5006
did not use

soln. in the presence of air) was 0.552 as compared to 1.120 for a control sample. The polymer also showed increased affinity for Astrazon Blue B dye. Vinylidene chloride is also used with II as a 3rd comonomer.

IT 27360-41-4, preparation 27360-42-5, preparation

RL: USES (Uses)

(dyeable fiber-forming heat-stable)

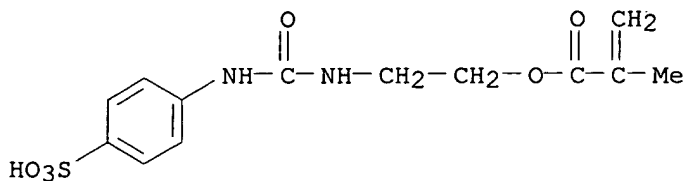
RN 27360-41-4 CAPLUS

CN Methacrylic acid, ester with sodium N-[(2-hydroxyethyl)carbamoyl]sulfanilate, polymer with acrylonitrile and methyl acrylate (8CI) (CA INDEX NAME)

CM 1

CRN 47242-55-7

CMF C13 H16 N2 O6 S . Na

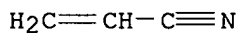


● Na

CM 2

CRN 107-13-1

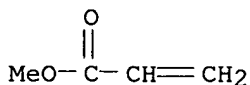
CMF C3 H3 N



CM 3

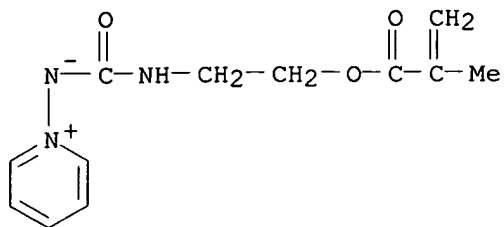
CRN 96-33-3

CMF C4 H6 O2



RN 27360-42-5 CAPLUS

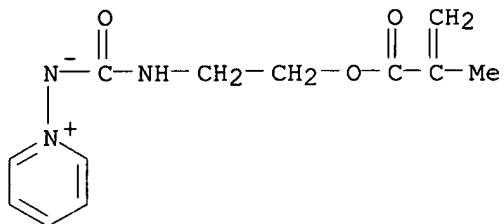
CN Methacrylic acid, ester with sodium N-[(2-hydroxyethyl)carbamoyl]sulfanilate, polymer with acrylonitrile (8CI) (CA INDEX NAME)



RN 102223-97-2 CAPLUS
 CN Pyridinium, 1-[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]carbonyl]a
 mino]-, inner salt, polymer with 2-[(ethoxycarbonyl)amino]ethyl
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

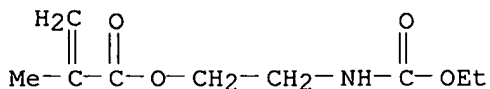
CM 1

CRN 102223-93-8
 CMF C12 H15 N3 O3



CM 2

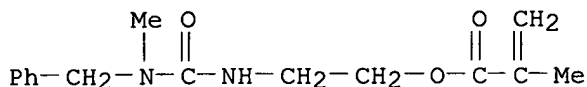
CRN 86291-20-5
 CMF C9 H15 N O4



L13 ANSWER 62 OF 69 CAPLUS COPYRIGHT 2002 ACS
 AN 1986:187171 CAPLUS
 DN 104:187171
 TI Ultraviolet spectroscopic determination of copolymer composition in
 IEM-containing copolymers
 AU Brown, Richard G.; Glass, J. Edward
 CS Polym. Coatings Dep., North Dakota State Univ., Fargo, ND, 58105, USA
 SO Polym. Mater. Sci. Eng. (1986), 54, 690-4
 CODEN: PMSEDG; ISSN: 0743-0515
 DT Journal
 LA English
 AB Compn. of isocyanatoethyl methacrylate(I)-Me methacrylate copolymer,
 prepd. by radical polymn., was detd. by UV spectroscopy of the
 benzylmethylamine(II) adduct. IR spectrum of I-II adduct homopolymer [
 101943-72-0] was similar to that of the polymer prepd. from the
 reaction of I homopolymer with II.

Did Not Use

IT 101943-72-0
 / RL: PRP (Properties)
 (UV spectra of,)
 RN 101943-72-0 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[[[methyl(phenylmethyl)amino]carbonyl]amino]ethyl ester, homopolymer (9CI) (CA INDEX NAME)
 CM 1
 CRN 101943-71-9
 CMF C15 H20 N2 O3



L13 ANSWER 63 OF 69 CAPLUS COPYRIGHT 2002 ACS
 AN 1985:555725 CAPLUS
 DN 103:155725
 TI Controlled activity polymers with pendent metribuzin. Effect of structure on hydrolytic release
 AU McCormick, Charles L.
 CS Dep. Polymer Sci., Univ. South. Mississippi, Hattiesburg, MS, 39406, USA
 SO Ann. N. Y. Acad. Sci. (1985), 446(Macromol. Drugs Carrier Biol. Act. Mater.), 76-92
 CODEN: ANYAA9; ISSN: 0077-8923
 DT Journal
 LA English
 AB Polymers with pendent metribuzin were prepd. from PVA, natural polysaccharides, and metribuzin-contg. acrylic monomers. These controlled-activity polymers were characterized by ¹³C NMR, IR, size exclusion chromatog., light scattering, and membrane osmometry. Release rates were measured in aq. soln. using reversed-phase liq. chromatog. with UV spectroscopy. Polymers with direct attachment to metribuzin through carbamate bonds exhibited slow release rates, esp. at a high degree of substitution, near a hydrophobic backbone, and at low pH values. Polymers with greatest hydrophilicity, spacer groups, urea bonds, and low DS values showed the fastest release, esp. at high pH. Acrylic polymers with amide bonds to pendent metribuzin showed increasingly faster rates with increasing degree of hydrolysis, addn. of spacer groups, and incorporation of hydrophilic monomers. Soil release studies and phytotoxicity tests are consistent with the obsd. levels in water. However, release rates for some systems prepd. from natural polysaccharides appear to be aided by soil microorganisms.

IT 76009-34-2P 98572-95-3P
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (prepn. of, as controlled-release herbicide)
 RN 76009-34-2 CAPLUS
 CN 2-Propenoic acid, 2-[[[6-(1,1-dimethylethyl)-3-(methylthio)-5-oxo-1,2,4-triazin-4(5H)-yl]amino]carbonyl]amino]ethyl ester, homopolymer (9CI) (CA INDEX NAME)
 CM 1
 CRN 76009-33-1
 CMF C14 H21 N5 O4 S

ER 35 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1996:73742 CAPLUS

DN 124:159878

TI Nonlinear optical material having azo-containing polymer and its manufacture

IN Nagamori, Hisatoshi; Tamura, Eri; Yashima, Hideo

PA Showa Denko Kk, Japan

SO Jpn. Kokai Tokkyo Koho, 9 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI	JP 07301833	A2	19951114	JP 1994-113534	19940428
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AB The material consists of (meth)acrylic acid ester-based polymers with mol. wt. 3000-100,000, contg. .gtoreq.0.1 mol% CH₂C(R₁)C(:O)O(CH₂)mR₂Ar(R₃)N:NA r(R₃)B [Ar = arom. group; R₁ = H, Me; R₂ = NR₄, NHCO₂(CH₂)m, NR₄, NHCONH, O, NHCO₂(CH₂)mO, NHCONH(CH₂)mO; R₃ = H, Me; R₄ = H, C1-6 alkyl, OH-terminated C1-6 oxyalkyl; B = electron attracting group; m = 1-6] and optionally CH₂C(R₁)C(:O)O(CH₂)mR₂ArR₃.

IT **173610-24-7DP**, azo coupling reaction products with diazonium salts
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(nonlinear optical material having azo-contg. (meth)acrylate polymer group)

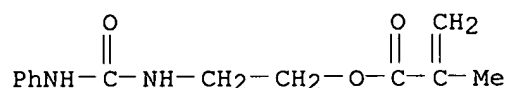
RN 173610-24-7 CAPLUS

-CN 2-Propenoic acid, 2-methyl-, 2-[[(phenylamino)carbonyl]amino]ethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 86219-42-3

CMF C13 H16 N2 O3



L13 ANSWER 38 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1995:602424 CAPLUS

DN 123:170508

TI Electroluminescent polymers containing pendant electroluminescent side chains, and electroluminescent devices containing them

IN Cumming, William J.; Gaudiana, Russell A.; Ingwall, Richard T.; Kolb, Eric S.; Mehta, Parag G.; Minns, Richard A.

PA Polaroid Corp., USA

SO U.S., 13 pp.

CODEN: USXXAM

DT Patent

LA English

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI	US 5414069	A	19950509	US 1993-12038	19930201
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AB An electroluminescent polymer consists of a main chain with at least 2 pendant electroluminescent side chains and a flexible spacer connecting the side chain with the main chain, such that the electroluminescent groups are not conjugated with each other. The main chain can be a

Gavel

polyether, polyurethane, polyimide, polyamide, polyurea, polyester, polyether ether ketone, poly(N-acylimine) or polysiloxane. Electroluminescent groups are chosen from anthracenyl, naphthacenyl, pentacenyl, fluoranthrenyl, tetrahydrochrysenyl, pyrenyl, carbazolyl, perylenyl, 1H-benzimidazo[2,1-a]benz[de]isoquinoliny, or 4-(2'-phenyl)vinylphenyl groups.

IT **167859-85-0P**

RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); SPN (Synthetic preparation); PREP (Preparation); USES (Uses) (polymers contg. pendant electroluminescent side chains, and electroluminescent devices contg. them)

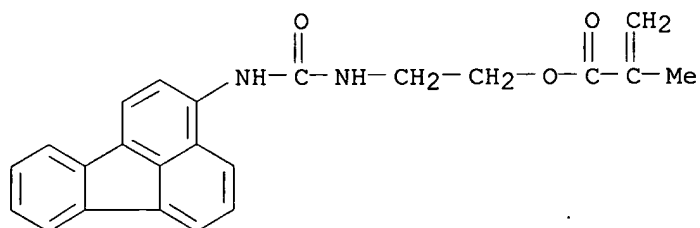
RN 167859-85-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(3-fluoranthrenylamino)carbonyl]amino]ethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 159802-39-8

CMF C23 H20 N2 O3



L13 ANSWER 39 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1995:499874 CAPLUS

DN 123:22208

TI Alkali-developable photosensitive composition and image formation using it

IN Kawamura, Koichi; Takita, Satoshi; Kawamura, Yoshitaka; Akyama, Keiji

PA Fuji Photo Film Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 22 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 07036185	A2	19950207	JP 1993-183023	19930723
	JP 3071611	B2	20000731		

AB The compn. contains a polymer obtained by polymn. of .gtoreq.1 vinyl-contg. benzoic acid deriv. I [A = H, halo, alkyl; X = O, NH, NR5; R1-4 = H, halo, (substituted) alkyl, (substituted) aryl, OR6, OCOR7, NHCOR8, NHCONHR9, OCONHR10, CO2R11, CONHR12, COR13, CONR14R15, CN, CHO; 2 of R1-4 may be form ring; R5 = alkyl; R6-15 = (substituted) alkyl, (substituted) aryl; L = divalent org. group] and a pos. photosensitive substance. Images are obtained by exposing a material having a photosensitive layer obtained from the compn. and developing with an alkali aq. soln. with pH .ltoreq.12.5. The compn. is useful for manuf. of lithog. printing plates, integrated circuits, photomasks, etc. The compn. gave lithog. printing plates with good printability.

IT **163588-53-2P**

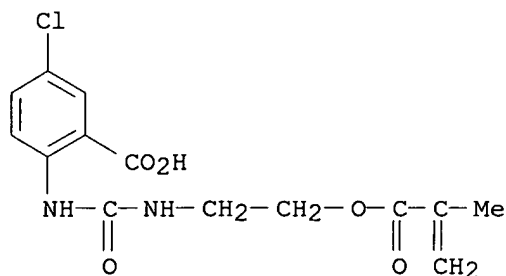
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (alkali-developable photoresist contg. benzoic acid deriv. polymer and

image formation using it)

RN 163588-53-2 CAPLUS
CN Benzoic acid, 5-chloro-2-[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]carbonyl]amino]-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 163588-52-1
CMF C14 H15 Cl N2 O5

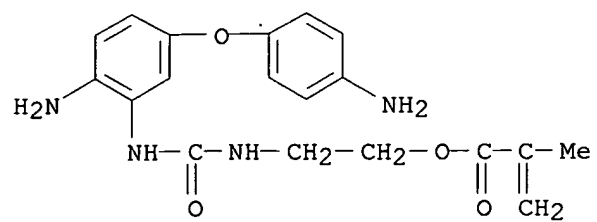


L13 ANSWER 41 OF 69 CAPLUS COPYRIGHT 2002 ACS
AN 1995:331225 CAPLUS
DN 122:226821
TI Heat-resistant photosensitive resin compositions
IN Hagiwara, Hideo; Kaji, Makoto; Kojima, Yasunori
PA Hitachi Chemical Co Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 7 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 06258833	A2	19940916	JP 1993-41082	19930302
AB	The resin compns. contain a polyamic acid ester having a repeating unit R1(NHCONHX)pNHCOR2(CO2Y)2CONH. The compns. have high photosensitivity and good coating characteristics. Thus, pyromellitic dianhydride, 3,3',4,4'-benzophenonetetracarboxylic acid dianhydride, and 2-hydroxyethyl methacrylate were reacted, followed by reaction with N-(2-methacryloyloxyethyl)-N'-[3-(4'-aminophenoxy)-6-aminophenyl]urea and 4,4'-diaminodiphenyl ether to give a polyamic acid ester. A resist of the polymer and photoinitiators gave high-quality patterns.				
IT	162215-88-5 RL: TEM (Technical or engineered material use); USES (Uses) (heat-resistant photosensitive resins)				
RN	162215-88-5 CAPLUS				
CN	2-Propenoic acid, 2-methyl-, 2-[[[2-amino-5-(4-aminophenoxy)phenyl]amino]carbonyl]amino]ethyl ester, polymer with 1H,3H-benzo[1,2-c:4,5-c']difuran-1,3,5,7-tetrone, 5,5'-carbonylbis[1,3-isobenzofurandione], 2-hydroxyethyl 2-methyl-2-propenoate and 4,4'-oxybis[benzenamine] (9CI) (CA INDEX NAME)				

CM 1

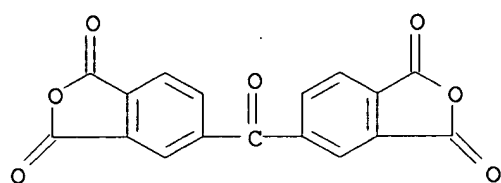
CRN 151668-82-5
CMF C19 H22 N4 O4



CM 2

CRN 2421-28-5

CMF C17 H6 O7



L13 ANSWER 27 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1999:565464 CAPLUS

DN 131:206998

TI Photosensitive composition and presensitized lithographic plate using same

IN Ishizuka, Yasuhiro; Hayakawa, Eiji; Oe, Koji

PA Dainippon Ink and Chemicals, Inc., Japan

SO Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11242325	A2	19990907	JP 1998-45214	19980226

AB The title compn. contains a photosensitive compd. in which .gtoreq.2 nos. of groups having urea or urethane bonds link through groups having biuret bonds. A presensitized lithog. plate is also claimed, comprising a metallic support coated with the compn. The compn. shows high contrast and improved developability, development latitude, and solvent resistance.

IT **184348-69-4**, 2-[N'-(4-Hydroxyphenylureido)ethyl methacrylate-methacrylamide-N-phenylmaleimide copolymer

RL: DEV (Device component use); USES (Uses)

(presensitized lithog. plate contg. photosensitive compn. contg.. urethane or urea compd. from biuret-type isocyanate)

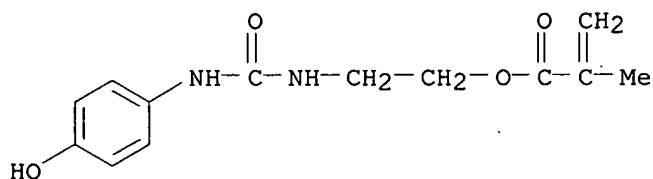
RN 184348-69-4 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(4-hydroxyphenyl)amino]carbonyl]amino]ethyl ester, polymer with 2-methyl-2-propenamide and 1-phenyl-1H-pyrrole-2,5-dione (9CI) (CA INDEX NAME)

CM 1

CRN 184348-63-8

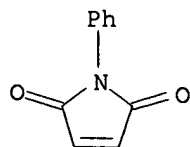
CMF C13 H16 N2 O4



CM 2

CRN 941-69-5

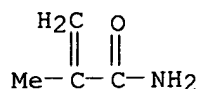
CMF C10 H7 N O2



CM 3

CRN 79-39-0

CMF C4 H7 N O



L13 ANSWER 28 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1999:530653 CAPLUS

DN 131:191918

TI Thermal recording material

IN Miura, Hidetoshi; Kubota, Kiyoko

PA Mitsubishi Paper Mills, Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 6 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11227340	A2	19990824	JP 1998-34965	19980217

OS MARPAT 131:191918

AB A thermal recording material with a thermosensitive color-forming layer contg. an electron-releasing dye precursor and an electron-withdrawing compd. represented by the formula I (R = H, alkyl, alkoxy, or the like) or its copolymer.

IT **240125-43-3 240125-44-4**

RL: TEM (Technical or engineered material use); USES (Uses)

(thermal recording materials contg. electron-releasing dye precursors and)

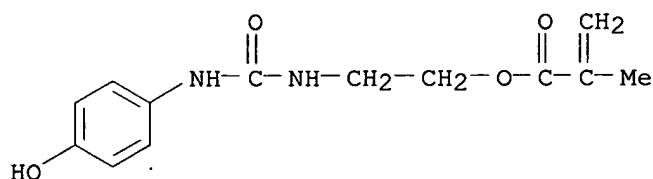
RN 240125-43-3 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(4-hydroxyphenyl)amino]carbonyl]amino]ethyl ester, polymer with 2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 184348-63-8

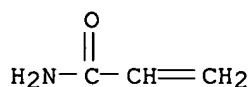
CMF C13 H16 N2 O4



CM 2

CRN 79-06-1

CMF C3 H5 N O

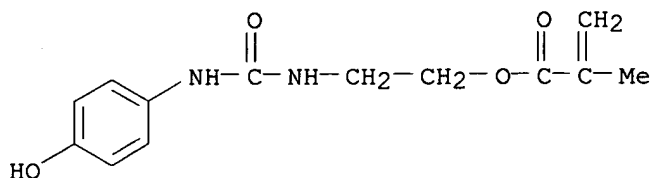


RN 240125-44-4 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[[[(4-hydroxyphenyl)amino]carbonyl]amino]ethyl ester, polymer with methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 184348-63-8

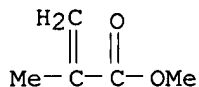
CMF C13 H16 N2 O4



CM 2

CRN 80-62-6

CMF C5 H8 O2



L13 ANSWER 30 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1999:244811 CAPLUS

DN 130:274097

TI Antireflection or light-absorbing coating and polymer therefor

IN Padmanaban, Munirathna; Kang, Wen-bing; Pawlowski, Georg; Kimura, Ken; Tanaka, Hatsuyuki

PA Clariant International Ltd., Switz.

SO PCT Int. Appl., 52 pp.

CODEN: PIXXD2

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9918478	A1	19990415	WO 1998-JP3789	19980826
	W: CN, KR, SG, US				
	RW: DE, FR, GB, IT				
	JP 11109640	A2	19990423	JP 1997-275652	19971008
	EP 942331	A1	19990915	EP 1998-940556	19980826
	R: DE, FR, GB, IT				
	US 6329117	B1	20011211	US 1999-319129	19990809
PRAI	JP 1997-275652	A	19971008		
	WO 1998-JP3789	W	19980826		

AB An antireflection or light-absorbing coating with good light absorption in the wavelength range of from 100 to 450 nm, free from footing and intermixing, and excellent in storage stability and step coverage and a novel copolymer therefor are disclosed. The copolymer is an acrylic or methacrylic copolymer comprising a main chain having carboxyl groups bonded to the carbon atoms thereof and, reaction-bonded thereto, at least (1) repeating units each comprising an aminated or hydroxylated org.

chromophore which absorbs light in the wavelength range of from 100 to 450 nm directly or through the -R1NHCXY- group (wherein R1 represents an alkylene group; X represents O or S; Y represents O or an NR2 group; and R2 represents H or a substituted or unsubstituted, straight-chain or cyclic alkyl or phenylene group) and (2) repeating units each comprising an alkyl group having a double bond or an epoxy group. A resist image having high resolu. can be formed by coating a wafer with the above coating to form a bottom antireflection coating, coating the surface of the coating with a photoresist, and then conducting exposure to far UV light and development.

IT 222032-28-2P 222032-30-6P 222032-34-0P
222172-98-7P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(prepn. and use in prep. underlaid antireflective layers for photoresists)

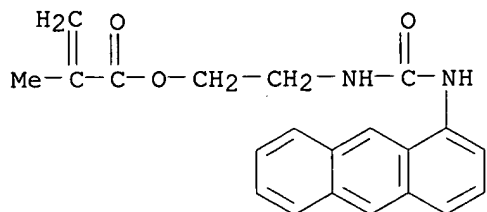
RN 222032-28-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(1-anthracenylamino)carbonyl]amino]ethyl ester, polymer with 2-[[[(9-anthracenylmethoxy)carbonyl]amino]ethyl 2-methyl-2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 222032-27-1

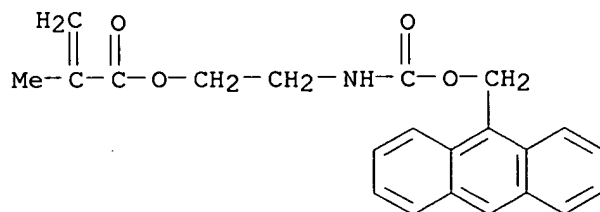
CMF C21 H20 N2 O3



CM 2

CRN 167859-78-1

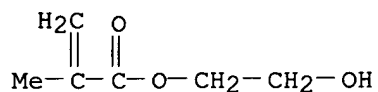
CMF C22 H21 N O4



CM 3

CRN 868-77-9

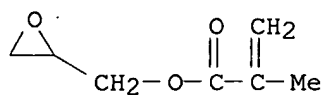
CMF C6 H10 O3



CM 4

CRN 106-91-2

CMF C7 H10 O3



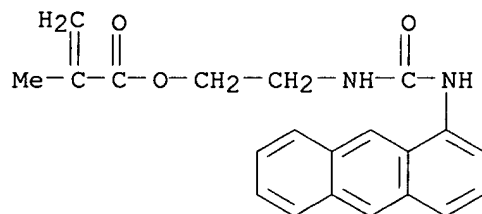
RN 222032-30-6 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(1-anthracenylamino)carbonyl]amino]ethyl ester, polymer with 2-propenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 222032-27-1

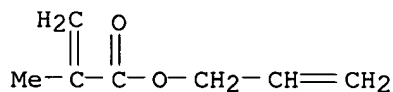
CMF C21 H20 N2 O3



CM 2

CRN 96-05-9

CMF C7 H10 O2



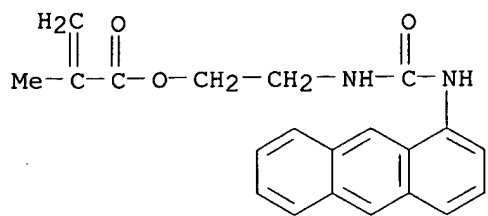
RN 222032-34-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(1-anthracenylamino)carbonyl]amino]ethyl ester, polymer with methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 222032-27-1

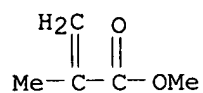
CMF C21 H20 N2 O3



CM 2

CRN 80-62-6

CMF C5 H8 O2



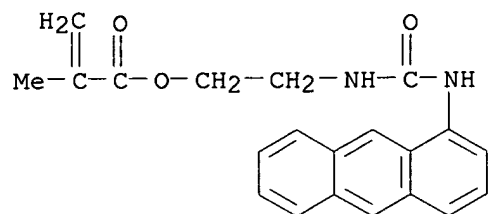
RN 222172-98-7 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(1-anthracenylamino)carbonyl]amino]ethyl ester, polymer with diethenylbenzene and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 222032-27-1

CMF C21 H20 N2 O3



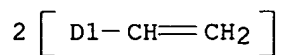
CM 2

CRN 1321-74-0

CMF C10 H10

CCI IDS

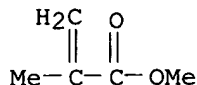
CDES 8:ID



CM 3

CRN 80-62-6

CMF C5 H8 O2



RE.CNT 24 THERE ARE 24 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L13 ANSWER 33 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1996:753778 CAPLUS

DN 126:24870

TI Photosensitive composition for planographic printing plate preparation

IN Ishizuka, Yasuhiro; Aburano, Maru; Hayakawa, Eiji; Oe, Koji

PA Dainippon Ink Chemical Industry Co., Japan

SO Eur. Pat. Appl., 25 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 737896	A2	19961016	EP 1996-105633	19960410
	EP 737896	A3	19970507		
	R: DE, FR, GB, NL				
	JP 08339080	A2	19961224	JP 1996-19911	19960206
	JP 08339082	A2	19961224	JP 1996-19912	19960206
	CA 2173638	AA	19961012	CA 1996-2173638	19960409
	US 5731127	A	19980324	US 1996-629613	19960409
PRAI	JP 1995-85345		19950411		
	JP 1995-85346		19950411		
	JP 1996-19911		19960206		
	JP 1996-19912		19960206		

AB A photosensitive compn. comprises a resin (A) having urea bonds in its side chains and a photosensitive compd. (B), wherein the resin (A) contains at least one resin selected from the group consisting of vinyl polymer resins and condensation polymer resins to provide a coating layer with excellent resistance to solvents and abrasion. The photosensitive compn. is suitable for use in the prodn. of planog. printing plates, integrated circuits, and photomasks. A planog. printing plate produced using the photosensitive compn. has superior press life.

IT **184348-65-0P 184348-66-1P 184348-67-2P**
184348-68-3P 184348-69-4P 184348-70-7P
184348-71-8P 184348-72-9P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(prepn. and use in photosensitive resin compns. for planog. plate manuf.)

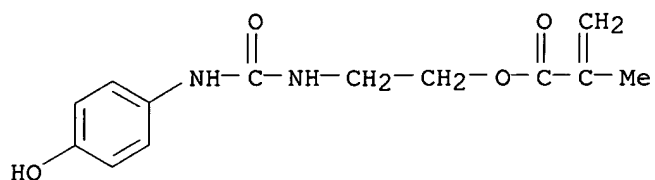
RN 184348-65-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with
2-[[[(4-hydroxyphenyl)amino]carbonyl]amino]ethyl 2-methyl-2-propenoate and
methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 184348-63-8

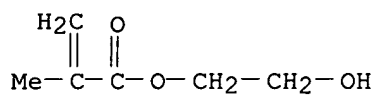
CMF C13 H16 N2 O4



CM 2

CRN 868-77-9

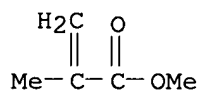
CMF C6 H10 O3



CM 3

CRN 80-62-6

CMF C5 H8 O2



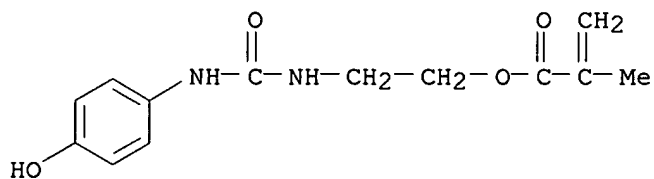
RN 184348-66-1 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with 2-[[[(4-hydroxyphenyl)amino]carbonyl]amino]ethyl 2-methyl-2-propenoate, 2-isocyanatoethyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 184348-63-8

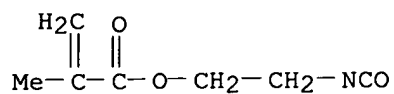
CMF C13 H16 N2 O4



CM 2

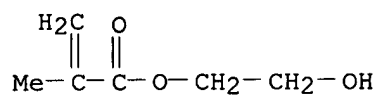
CRN 30674-80-7

CMF C7 H9 N O3



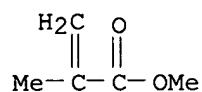
CM 3

CRN 868-77-9
CMF C6 H10 O3



CM 4

CRN 80-62-6
CMF C5 H8 O2

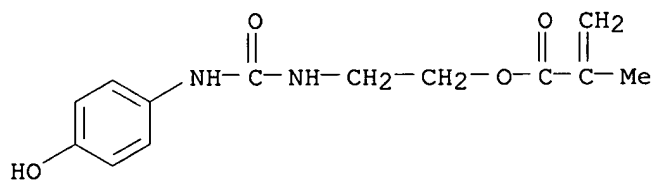


RN 184348-67-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(4-hydroxyphenyl)amino]carbonyl]amino]ethyl ester, polymer with 1-phenyl-1H-pyrrole-2,5-dione (9CI) (CA INDEX NAME)

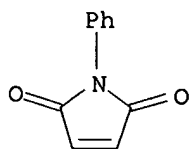
CM 1

CRN 184348-63-8
CMF C13 H16 N2 O4



CM 2

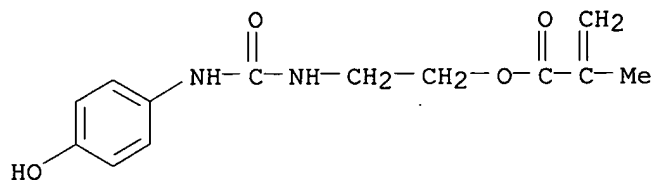
CRN 941-69-5
CMF C10 H7 N O2



RN 184348-68-3 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[[[(4-hydroxyphenyl)amino]carbonyl]amino]ethyl ester, polymer with 2-methyl-2-propenamide and 2-propenenitrile (9CI)
 (CA INDEX NAME)

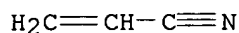
CM 1

CRN 184348-63-8
 CMF C13 H16 N2 O4



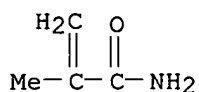
CM 2

CRN 107-13-1
 CMF C3 H3 N



CM 3

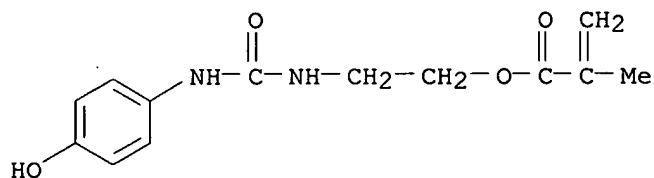
CRN 79-39-0
 CMF C4 H7 N O



RN 184348-69-4 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[[[(4-hydroxyphenyl)amino]carbonyl]amino]ethyl ester, polymer with 2-methyl-2-propenamide and 1-phenyl-1H-pyrrole-2,5-dione (9CI) (CA INDEX NAME)

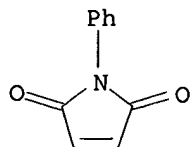
CM 1

CRN 184348-63-8
 CMF C13 H16 N2 O4



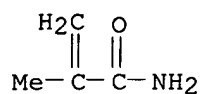
CM 2

CRN 941-69-5
CMF C10 H7 N O2



CM 3

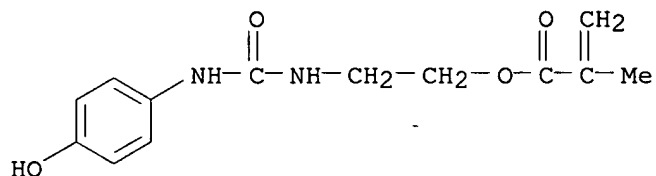
CRN 79-39-0
CMF C4 H7 N O



RN 184348-70-7 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[[[(4-hydroxyphenyl)amino]carbonyl]amino]ethyl ester, polymer with methyl 2-methyl-2-propenoate, 2-methyl-2-propenamide and 2-propenenitrile (9CI) (CA INDEX NAME)

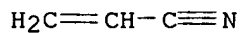
CM 1

CRN 184348-63-8
CMF C13 H16 N2 O4



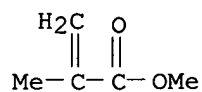
CM 2

CRN 107-13-1
CMF C3 H3 N



CM 3

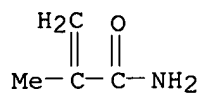
CRN 80-62-6
CMF C5 H8 O2



CM 4

CRN 79-39-0

CMF C4 H7 N O



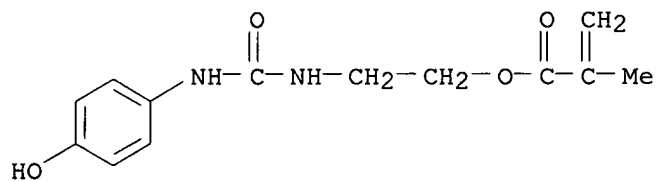
RN 184348-71-8 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(4-hydroxyphenyl)amino]carbonyl]amino]ethyl ester, polymer with 2-methyl-2-propenamide, 1-phenyl-1H-pyrrole-2,5-dione and 2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 184348-63-8

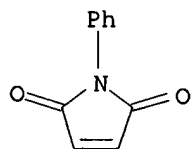
CMF C13 H16 N2 O4



CM 2

CRN 941-69-5

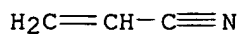
CMF C10 H7 N O2



CM 3

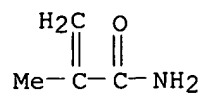
CRN 107-13-1

CMF C3 H3 N



CM 4

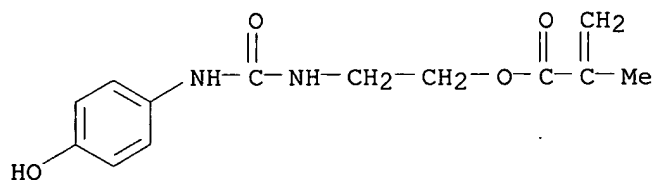
CRN 79-39-0
CMF C4 H7 N O



RN 184348-72-9 CAPLUS
CN 2-Propenoic acid, 2-methyl-, polymer with 2-[[[(4-hydroxyphenyl)amino]carbonyl]amino]ethyl 2-methyl-2-propenoate, 2-methyl-2-propenamide and 2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 184348-63-8
CMF C13 H16 N2 O4



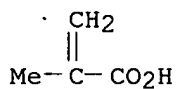
CM 2

CRN 107-13-1
CMF C3 H3 N



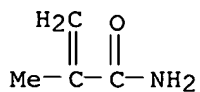
CM 3

CRN 79-41-4
CMF C4 H6 O2

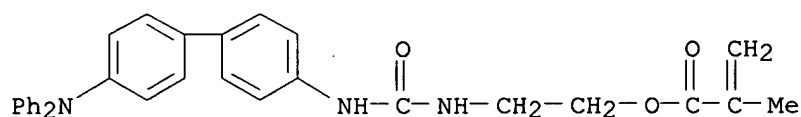


CM 4

CRN 79-39-0
CMF C4 H7 N O



L13 ANSWER 34 OF 69 CAPLUS COPYRIGHT 2002 ACS
 AN 1996:136099 CAPLUS
 DN 124:178244
 TI A New Polymeric Triarylamine and Its Use as a Charge Transport Layer for Polymeric LEDs
 AU Kolb, Eric S.; Gaudiana, Russell A.; Mehta, Parag G.
 CS Materials Research Laboratory, Polaroid Corporation, Cambridge, MA, 02139, USA
 SO Macromolecules (1996), 29(7), 2359-64
 CODEN: MAMOBX; ISSN: 0024-9297
 DT Journal
 LA English
 AB A new hole-injecting polymer for an electroluminescent element was prepd. by radical polymn. of a methacrylate monomer that contains an N'-biphenyl-N,N-diphenylamine unit as a pendent side chain. Cyclic voltammetry of the polymer coated on an ITO electrode shows a chem. irreversible oxidn. at 1.2 V. Subsequent cycles reveal that the newly formed species is electrochem. stable. The polymer was used as both an electroluminescent layer and a hole injection layer in single- and double-layered devices, resp. The double-layered device using ITO as the anode, Al as the cathode, and poly[methyl(2-(1-pyrenyl)ethyl)siloxane] as the electroluminescent layer gave bright blue-green light with a max. brightness level of 168 cd/m2 and an internal quantum efficiency of 0.20%.
 IT **173865-99-1P**
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (polymeric triarylamine and for hole injection in charge transport layer for polymeric LEDs)
 RN 173865-99-1 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[[[4'-(diphenylamino)[1,1'-biphenyl]-4-yl]amino]carbonyl]amino]ethyl ester, homopolymer (9CI) (CA INDEX NAME)
 CM 1
 CRN 173865-98-0
 CMF C31 H29 N3 O3



=>

L29 ANSWER 10 OF 17 CAPLUS COPYRIGHT 2002 ACS

AN 1998:795188 CAPLUS

DN 130:45293

TI Composition for antireflection or light absorption film and compounds for use in same

IN Padmanaban, Munirathna; Kang, Wen-bing; Tanaka, Hatsuyuki; Kimura, Ken; Pawlowski, Georg

PA Clariant International Ltd., Switz.

SO PCT Int. Appl., 65 pp.

CODEN: PIXXD2

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9854619	A1	19981203	WO 1998-JP2234	19980521
	W: CN, JP, KR, SG, US				
	RW: DE, FR, GB, IT				
	EP 917002	A1	19990519	EP 1998-921751	19980521
	R: DE, FR, GB, IT				
	KR 2000029602	A	20000525	KR 1999-700666	19990126
PRAI	JP 1997-137088	A	19970527		
	WO 1998-JP2234	W	19980521		

AB A compn. capable of forming an antireflection or light absorption film which satisfactorily absorbs radiations having wavelengths of 100 to 450 nm, is free from the diffusion of a photo-generated acid into the film or the intermixing of a resist with the film, and is excellent in storage stability and step coverage properties; and novel compds. and novel polymers useful for the compn. The compn. contains a compd. which is a (meth)acrylic monomer or polymer having at least one isocyanate or thioisocyanate group bonded to a side chain thereof through an alkylene group, etc., or contains the compd. or polymer which has an aminated or hydroxylated org. chromophore which absorbs light in the wavelength region of 100 to 450 nm and is bonded to the isocyanate or thioisocyanate group. The compn. is applied to a substrate and baked to form a film serving as, e.g., an antireflection film. A chem.-amplification-type resist is applied to this film, and the resist film is exposed to light and then developed to form a resist image with high resoln. Due to the presence of the isocyanate or thioisocyanate group in the compd., the film serving as, e.g., an antireflection film is cured through crosslinking during baking. Due to the presence of the org. chromophore, the film absorbs exposure light in the wavelength region of 100 to 450 nm.

IT **216989-12-7P**, N-(2-Methacryloyloxyethyl)-9-methylanthracene carbamate-2-methacryloyloxyethyl acetate copolymer **216989-14-9P**, N-(2-Methacryloyloxyethyl)-9-methylanthracene carbamate-methyl methacrylate-methacryloyloxyethyl isocyanate copolymer
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(compn. for antireflection or light absorption film)

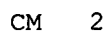
RN 216989-12-7 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(acetyloxy)ethyl ester, polymer with 2-[[[(9-anthracenylmethoxy)carbonyl]amino]ethyl 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

CM 1

CRN 167859-78-1

CMF C22 H21 N O4



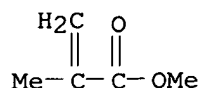
RN 216989-14-9 CAPLUS

CM 1

CM 2

CM 3

CRN 80-62-6
CMF C5 H8 O2



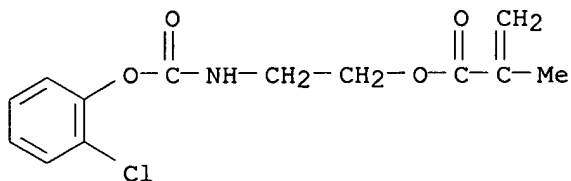
RE.CNT 25 THERE ARE 25 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L29 ANSWER 11 OF 17 CAPLUS COPYRIGHT 2002 ACS
AN 1995:630118 CAPLUS
DN 123:22145
TI Electrophotographic lithographic printing plate master
IN Tashiro, Hiroshi; Kato, Eiichi
PA Fuji Photo Film Co Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 57 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 07084379	A2	19950331	JP 1993-253695	19930917
AB	The title printing plate master has on its elec. conductive support .gtoreq.1 photo-conducting layer contg. (1)a binder resin(A) that is based on a monomer capable of giving CO2H, a monomer capable of giving SO3H, SO2H, or PO3H3, and a monomer contg. heat/photo curable group, (2)a non-aq. solvent dispersed resin particle(B) that is obtained by dispersion-polymg. a monomer contg. a polar group insol. after polymn., a Si- or F-contg. monomer, and a monomer having a double bond at its end in the presence of a dispersion stabilizing resin, and (3) a photoconductive compd. The invention plate master can be used in various printer to give high quality printing without background stains and paper damage.				
IT	156623-48-2 RL: DEV (Device component use); USES (Uses) (binder for electrophotog. lithog. printing plate master)				
RN	156623-48-2 CAPLUS				
CN	Hexanoic acid, 3-[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl)sulfonyl]oxy]-, phenyl ester, polymer with 2-[[[2-chlorophenoxy)carbonyl]amino]ethyl 2-methyl-2-propenoate and 1,1-dimethyl-3-oxoheptyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)				

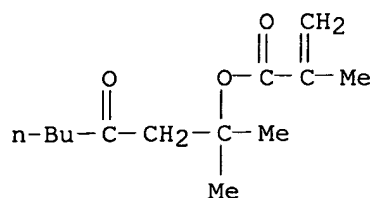
CM 1

CRN 155839-20-6
CMF C13 H14 Cl N O4



CM 2

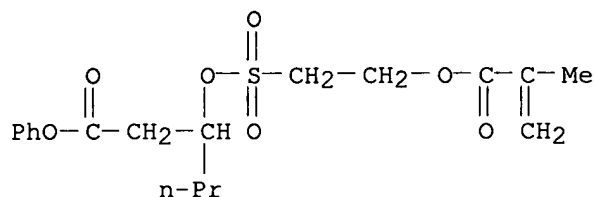
CRN 155839-16-0
CMF C13 H22 O3



CM 3

CRN 155839-15-9

CMF C18 H24 O7 S



L29 ANSWER 12 OF 17 CAPLUS COPYRIGHT 2002 ACS

AN 1995:490229 CAPLUS

DN 122:326592

TI **Photosensitive** composition containing sulfoneimide polymer

IN Kawamura, Koichi

PA Fuji Photo Film Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 26 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 07028242	A2	19950131	JP 1993-168111	19930707
	JP 3078152	B2	20000821		

AB The compn. contains a polymer contg. sulfonimide group LSO2NR2SO2R1 [R1, R2 = (substituted) arom. group, (substitute) alkyl; L = bond to polymer]. The polymer generates free radicals or acids by irradiation. The compn. is esp. useful for manuf. of printing plates without development process.

IT **163427-98-3**

RL: PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)

(**photosensitive** compn. contg. sulfoneimide polymer for printing original plates)

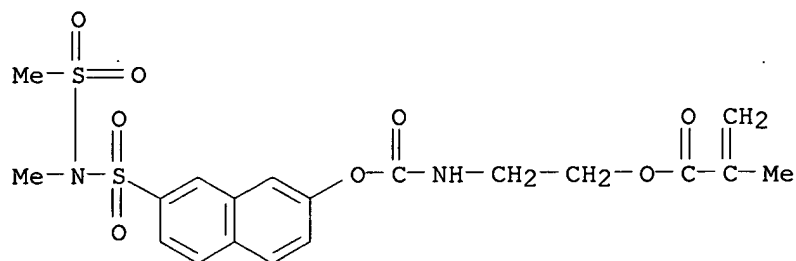
RN 163427-98-3 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[7-[[methyl(methylsulfonyl)amino]sulfonyl]-2-naphthalenyl]oxy]carbonyl]amino]ethyl ester, polymer with oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

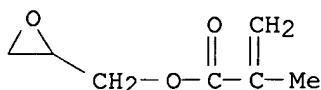
CRN 163427-97-2

CMF C19 H22 N2 O8 S2



CM 2

CRN 106-91-2
CMF C7 H10 O3



L29 ANSWER 13 OF 17 CAPLUS COPYRIGHT 2002 ACS

AN 1994:711863 CAPLUS

DN 121:311863

TI Electrophotographic photoreceptor sheet used in lithographic platemaking

IN Kato, Eiichi; Tashiro, Hiroshi; Ishii, Kazuo

PA Fuji Photo Film Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 65 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 06027750	A2	19940204	JP 1992-201812	19920707

AB In the title electrophotog. photoreceptor sheet comprising a conductive support, a photoconductive layer incorporating a photoconductor compd. and a binder resin, and a claimed surface layer, the latter contains a binder resin(s) (A) and the **photosensitive** layer contains a binder resin(s) (B). Binder resin (A) contains a polymer component(s) which yields .gtoreq.1 CO2H on reaction, a component(s) which yields .gtoreq.1 selected from SO3H, SO2H, and PO3H, and .gtoreq.1 components which yield thermo- or photohardenable groups on reaction. Binder resin (B) (wt. av. mol. wt. 1 x 103-2 x 104) possesses the structural repeating unit CHa1Ca2(CO2Q3) [a1,a2 = H, halo, CN, hydrocarbyl; Q3 = hydrocarbyl] .gtoreq.30%, and polar groups selected from PO3H, SO3H, P(O)(OH)Q1 [Q1 = hydrocarbyl, Q2 (Q2 = hydrocarbyl)], and cyclic acid anhydride are present in the polymer chain or at 1 end of the polymer chain. The photoreceptor sheet resists background soiling, has superior desensitization characteristics, and gives highly durable lithog. plates.

IT 155838-53-2P

RL: DEV (Device component use); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (binder resin; Electrophotog. photoreceptor sheet used in lithog. platemaking)

RN 155838-53-2 CAPLUS

CN Butanoic acid, 4-mercapto-, telomer with 2-chloro-5-methylphenyl 2-methyl-2-propenoate and 2-[(phenoxycarbonyl)amino]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 13095-73-3

CMF C4 H8 O2 S

HS-(CH₂)₃-CO₂H

CM 2

CRN 155838-52-1

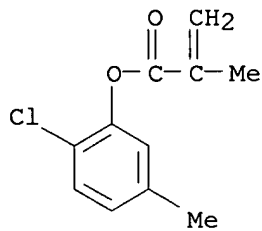
CMF (C13 H15 N O4 . C11 H11 Cl O2)x

CCI PMS

CM 3

CRN 155246-91-6

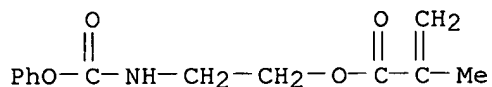
CMF C11 H11 Cl O2



CM 4

CRN 89819-91-0

CMF C13 H15 N O4



IT 159320-06-6P

RL: DEV (Device component use); SPN (Synthetic preparation); PREP

(Preparation); USES (Uses)

(electrophotog. photoreceptor sheet surface layer contg.)

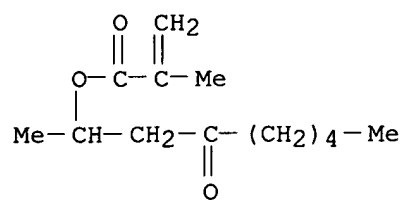
RN 159320-06-6 CAPLUS

CN Hexanoic acid, 3-[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]sulfonyl]oxy]-, phenyl ester, polymer with 2-[[[(2-chlorophenoxy)carbonyl]amino]ethyl 2-methyl-2-propenoate, 2,3-dihydroxypropyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate and 1-methyl-3-oxooctyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 159320-00-0

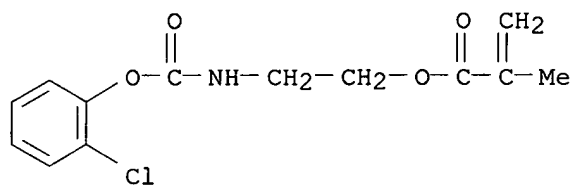
CMF C13 H22 O3



CM 2

CRN 155839-20-6

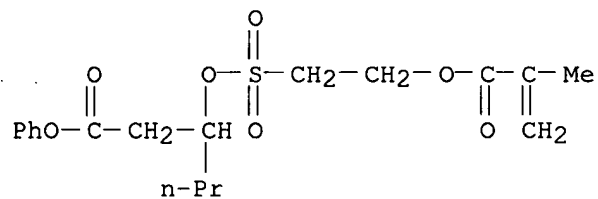
CMF C13 H14 Cl N O4



CM 3

CRN 155839-15-9

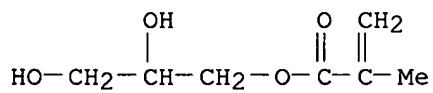
CMF C18 H24 O7 S



CM 4

CRN 5919-74-4

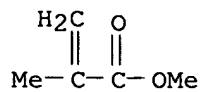
CMF C7 H12 O4

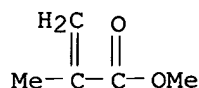


CM 5

CRN 80-62-6

CMF C5 H8 O2





L29 ANSWER 14 OF 17 CAPLUS COPYRIGHT 2002 ACS

AN 1993:637954 CAPLUS

DN 119:237954

TI Electrophotographic material for color proofing

IN Kato, Eiichi; Osawa, Sadao

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 165 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 534479	A1	19930331	EP 1992-116494	19920925
	EP 534479	B1	19981209		
	R: DE, GB				
	JP 05197169	A2	19930806	JP 1992-310754	19920928
	US 5670283	A	19970923	US 1994-279068	19940722
PRAI	JP 1991-249819		19910927		
	JP 1991-259430		19911007		
	JP 1991-289648		19911106		
	JP 1991-289649		19911106		
	US 1992-952941		19920928		

AB An electrophotog. material for color proofing comprises a substrate, a photoconductive layer and a transfer layer in this order, and is used for prep. a color proof in a process wherein at least one color toner image is electrophotog. formed on the transfer layer and then transferred together with said transfer layer to a sheet material to prep. the color proof, wherein said photoconductive layer comprises a copolymer and/or a crosslinked polymer particle which contain units having F atom(s) and/or Si atom(s) at least in the region near the surface facing said transfer layer and the surface of said photoconductive layer which contacts with the transfer layer has tack strength of .ltoreq.150 g .cntdot. force, which is measured by Pressure Sensitive Tape and Sheet Test of JIS Z0237-1980.

IT **150625-82-4P**

RL: SPN (Synthetic preparation); PREP (Preparation)

(prepn. and use of, in electrophotog. plate, for reduced tack)

RN 150625-82-4 CAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with ethyl 2-methyl-2-propenoate, 2-[[(2-methylphenoxy) carbonyl] amino] ethyl 2-methyl-2-propenoate, 2- (phosphonoxy) ethyl 2-methyl-2-propenoate and 3- (undecamethylpentasiloxanyl) propyl 2-methyl-2-propenoate, block, graft (9CI) (CA INDEX NAME)

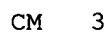
CM 1

CRN 150625-81-3

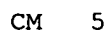
CMF C14 H17 N O4



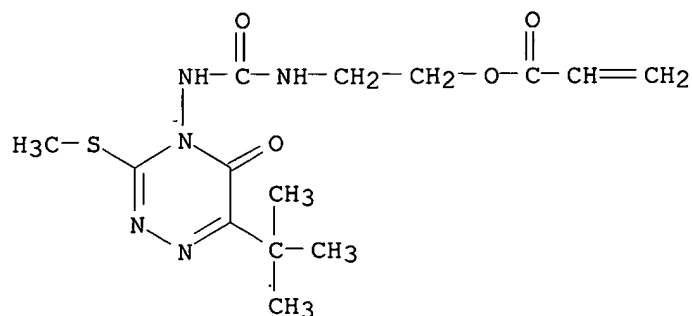
CMF C18 H44 O6 Si5



CMF C6 H11 O6 P

CMFC8H14O2

CMF C6 H10 O2



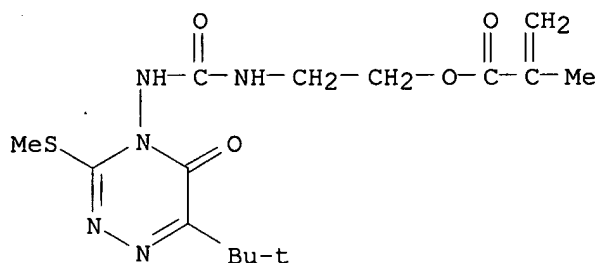
RN 98572-95-3 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[6-(1,1-dimethylethyl)-3-(methylthio)-5-oxo-1,2,4-triazin-4(5H)-yl]amino]carbonyl]amino]ethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 98572-94-2

CMF C15 H23 N5 O4 S



L13 ANSWER 64 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1981:516041 CAPLUS

DN 95:116041

TI Polymeric chelating ligands derived from 1,3-bis(2'-pyridylimino)isoindolines

AU Siegl, Walter O.

CS Eng. Res. Staff, Ford Motor Co., Dearborn, MI, 48121, USA

SO Chem. Ind. (London) (1981), (8), 291-2

CODEN: CHINAG; ISSN: 0009-3068

DT Journal

LA English

AB 4-Nitrophthalonitrile [31643-49-9] underwent CaCl_2 -facilitated condensation with 2-amino-4-methylpyridine [695-34-1] to give 79% of the isoindoline deriv. I (R = NO_2) [78696-54-5], which on redn. with H (60 psi H, EtOH, 10% Pd/C, 25.degree.) gave 90% I (R = NH_2) (II) [78696-55-6]. Treatment of II with a chlorosulfonated styrene-divinylbenzene copolymer led to a max. loading of 15% based on the N:S ratio. II with $\text{CH}_2:\text{CMeCOCl}$ [920-46-7] and $\text{CH}_2:\text{CMeCO}_2(\text{CH}_2)_2\text{NCO}$ [30674-80-7] gave 68% I (R = NHCOCMe:CH_2) (III) [78696-56-7] and 67% I [R = $\text{NHCONH}(\text{CH}_2)_2\text{O}_2\text{CCMe:CH}_2$] (IV) [78696-57-8], resp. III and IV polymd. in DMF at 60-70.degree. to give 65% III homopolymer [78705-29-0] and 86% IV homopolymer [78705-30-3], resp. The 2 homopolymers reacted with Cu^{2+} to give complexes in which 94 and 77% of the chelating sites, resp., were occupied by Cu^{2+} .

IT 78705-30-3DP, copper complexes 78705-30-3P

RL: SPN (Synthetic preparation); PREP (Preparation)

(prepn. of)

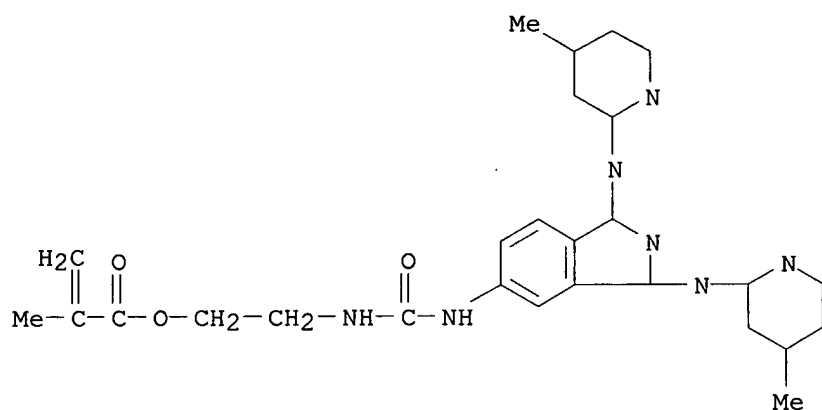
RN 78705-30-3 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[3-[(4-methyl-2-pyridinyl)amino]-1-[(4-methyl-2-pyridinyl)imino]-1H-isoindol-5-yl]amino]carbonyl]amino]ethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 78696-57-8

CMF C27 H27 N7 O3



*** FRAGMENT DIAGRAM IS INCOMPLETE ***

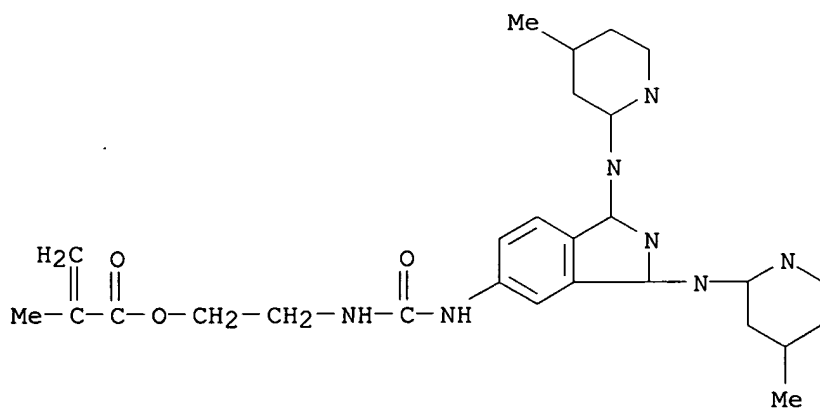
RN 78705-30-3 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[3-[(4-methyl-2-pyridinyl)amino]-1-[(4-methyl-2-pyridinyl)imino]-1H-isoindol-5-yl]amino]carbonyl]amino]ethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 78696-57-8

CMF C27 H27 N7 O3



*** FRAGMENT DIAGRAM IS INCOMPLETE ***

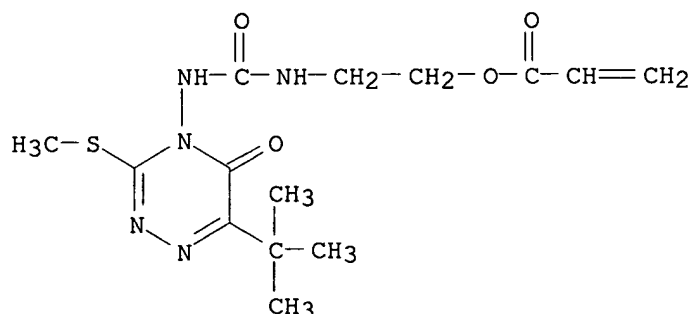
L13 ANSWER 65 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1981:97833 CAPLUS

DN 94:97833

TI Controlled activity polymers with labile bonds to pendent metribuzin

AU McCormick, C. L.; Fooladi, M. M.
 CS Dep. Polym. Sci., Univ. South. Mississippi, Hattiesburg, MS, USA
 SO Controlled Release Bioact. Mater., [Symp. Int. Meet. Controlled Release Soc.], 6th (1980), Meeting Date 1979, 317-30. Editor(s): Baker, Richard W. Publisher: Academic, New York, N. Y.
 CODEN: 44VLAG
 DT Conference
 LA English
 AB The synthesis, characterization, and hydrolysis of metribuzin (I) [21087-64-9]-contg. polymers with carbamate, urea, and amide bonds are described. The electronic nature of the triazine ring and its proximity to the urea or amide bond leads to rapid rates of hydrolysis in distd. water. Polymers prepd. from the methacrylic monomer exhibited release rates similar to those prepd. from the acrylic monomer.
 IT **76009-34-2**
 RL: RCT (Reactant)
 (characterization and hydrolysis and synthesis of)
 RN 76009-34-2 CAPLUS
 CN 2-Propenoic acid, 2-[[[6-(1,1-dimethylethyl)-3-(methylthio)-5-oxo-1,2,4-triazin-4(5H)-yl]amino]carbonyl]amino]ethyl ester, homopolymer (9CI) (CA INDEX NAME)
 CM 1
 CRN 76009-33-1
 CMF C14 H21 N5 O4 S



L13 ANSWER 66 OF 69 CAPLUS COPYRIGHT 2002 ACS
 AN 1981:42655 CAPLUS
 DN 94:42655
 TI Pesticide-polymer systems prepared from vinyl monomers
 IN McCormick, Charles L.
 PA USA
 SO U.S., 10 pp.
 CODEN: USXXAM
 DT Patent
 LA English
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 4225693	A	19800930	US 1978-932724	19780810

AB An acrylic acid deriv. is reacted with a pesticide or a pesticide deriv. having an active H, to give a vinyl monomer, which upon polymn. gives a controlled-release pesticide polymer. Thus, 200 parts THF, 7.2 parts acrylamide [79-06-1], and 15 parts trimethylpyridine were heated to 30-5.degree. for 0.5 h, followed by the addn. of 50 parts THF and 25 parts 2,4-D acid chloride [774-74-3], to give I [76009-19-3], m. 120.degree..

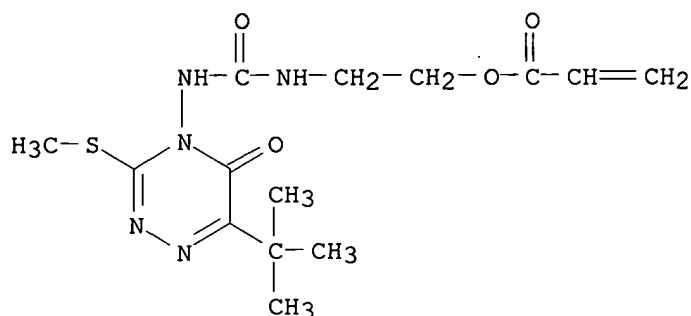
I was polymd. in the presence of Bz2O2 to give a 2,4-D-releasing polymer.

IT **76009-34-2P**
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (prepn. of, as controlled-release pesticide polymer)

RN 76009-34-2 CAPLUS
 CN 2-Propenoic acid, 2-[[[6-(1,1-dimethylethyl)-3-(methylthio)-5-oxo-1,2,4-triazin-4(5H)-yl]amino]carbonyl]amino]ethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 76009-33-1
 CMF C14 H21 N5 O4 S



L13 ANSWER 67 OF 69 CAPLUS COPYRIGHT 2002 ACS
 AN 1973:85651 CAPLUS
 DN 78:85651
 TI Synthesis of new unsaturated comonomers and their copolymerization with acrylonitrile
 AU Bahr, Ulrich; Wieden, Horst; Rinkler, Heinrich August; Nischk, Guenther
 CS Org.-Wiss. Lab., Farbenfabr. Bayer A.-G., Dormagen/Rhein, Ger.
 SO Makromol. Chem. (1972), 161, 1-47
 CODEN: MACEAK
 DT Journal
 LA German
 AB Methacrylates and methacrylamides contg. tertiary amino, pyridyl, and picolinyl substituents, methacrylic acid hydrazides, unsatd. compds. contg. the [2[(2,2-dimethylhydrazino)carbonyl]phenyl]carbamoyl group, unsatd. derivs. of oxalic acid hydrazide, ammonium salts and sulfobetaines of all these compds., and unsatd. semicarbazide derivs. and their quaternized salts were prepd. and copolymd. with acrylonitrile to give fiber-forming copolymers with high hydrophilicity and improved acid dyeability and, or the sulfobetaines, basic dyeability. Typical compds. prepd. were N-(2-methacryloyloxyethyl)-N'-[3-(diethylamino)propyl]urea [37780-53-3], 3-(1,1-dimethyl-2-methacryloyl-1-hydrazinium)-1-propanesulfonate [19659-68-8], 3-(methacrylamido)benzoic acid N',N'-dimethylhydrazide [14613-10-6], oxalic acid N-[(methacrylamido)methyl]amide N,N'-dimethylhydrazide [14254-32-1], and N1-(2-methacryloyloxyethyl)-N3,N3-dimethylsemicarbazide [13041-22-0]. Heat-crimpable fibers were prepd. by cospinning the modified acrylic polymers with acrylonitrile copolymers contg. no ionic groups.

IT **34977-10-1P 40854-41-9P 40854-42-0P**
40854-43-1P 40854-44-2P 40854-45-3P
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (prepn. of)

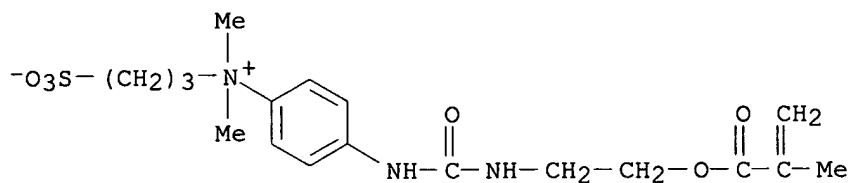
RN 34977-10-1 CAPLUS
 CN Benzenaminium, N,N-dimethyl-4-[[[2-[(2-methyl-1-oxo-2-

propenyl)oxy]ethyl]amino]carbonyl]amino]-N-(3-sulfopropyl)-, inner salt,
polymer with 2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 5205-97-0

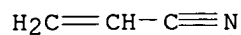
CMF C18 H27 N3 O6 S



CM 2

CRN 107-13-1

CMF C3 H3 N



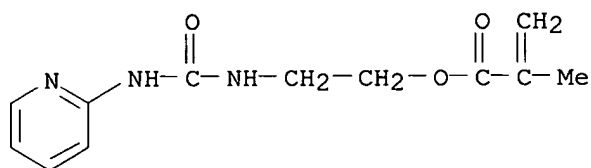
RN 40854-41-9 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(2-pyridinylamino)carbonyl]amino]ethyl
ester, polymer with 2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 13001-27-9

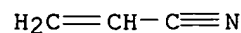
CMF C12 H15 N3 O3



CM 2

CRN 107-13-1

CMF C3 H3 N

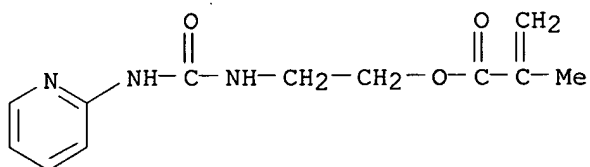


RN 40854-42-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(2-pyridinylamino)carbonyl]amino]ethyl
ester, polymer with methyl 2-propenoate and 2-propenenitrile (9CI) (CA
INDEX NAME)

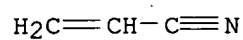
CM 1

CRN 13001-27-9
CMF C12 H15 N3 O3



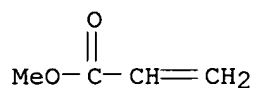
CM 2

CRN 107-13-1
CMF C3 H3 N



CM 3

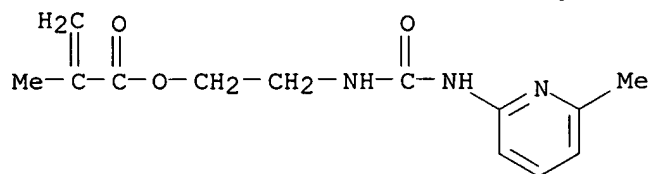
CRN 96-33-3
CMF C4 H6 O2



RN 40854-43-1 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[[[(6-methyl-2-pyridinyl)amino]carbonyl]amino]ethyl ester, polymer with 2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 13041-21-9
CMF C13 H17 N3 O3



CM 2

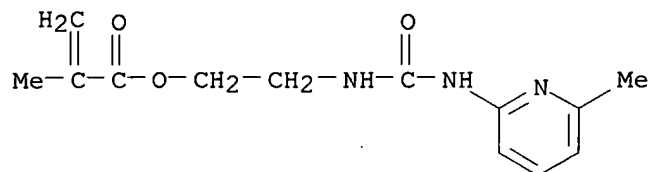
CRN 107-13-1
CMF C3 H3 N



RN 40854-44-2 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[[[(6-methyl-2-pyridinyl)amino]carbonyl]amino]ethyl ester, polymer with methyl 2-propenoate and 2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 13041-21-9
 CMF C13 H17 N3 O3



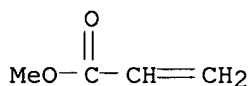
CM 2

CRN 107-13-1
 CMF C3 H3 N



CM 3

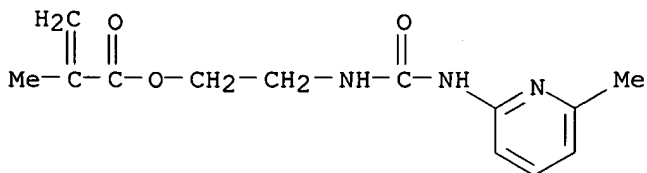
CRN 96-33-3
 CMF C4 H6 O2



RN 40854-45-3 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[[[(6-methyl-2-pyridinyl)amino]carbonyl]amino]ethyl ester, polymer with 4-methylbenzenesulfonic acid, methyl 2-propenoate and 2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 13041-21-9
 CMF C13 H17 N3 O3



CM 2

CRN 107-13-1

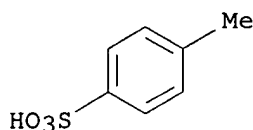
CMF C3 H3 N



CM 3

CRN 104-15-4

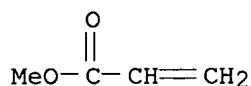
CMF C7 H8 O3 S



CM 4

CRN 96-33-3

CMF C4 H6 O2



L13 ANSWER 68 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1972:15194 CAPLUS

DN 76:15194

TI Copolymers of acrylonitrile with sulfobetaines

IN Szita, Jenö; Bahr, Ulrich; Wieden, Horst; Marzolph, Herbert; Nischk, Gunther

PA Farbenfabriken Bayer A.-G.

SO Brit. Amended, 10 pp. See Belg. 659,316, CA 64, 3805e.

CODEN: BSXXAH

DT Patent

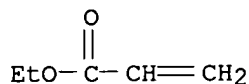
LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	GB 1024029		19690514		
PRAI	DE		19640206		

AB Acrylonitrile (I) was copolymerized with 1-10 wt. percent of [2-(methacryloyloxy)ethyl]dimethyl(3-sulfopropyl)ammonium hydroxide inner salt (II), [2-(methacryloylamino)ethyl]dimethyl(3-sulfopropyl)ammonium hydroxide inner salt, or 2-[3-[.alpha.-(methacryloyloxy)ethyl]ureido]-1-(3-sulfopropyl)pyridinium hydroxide inner salt to give copolymers, useful in the manufacture of dyeable films and fibers. Thus, a pH 3.5 H₂SO₄ soln. of a 95:5(wt. ratio) I-II mixt. was polymerized 3 hr at 50.deg. in the presence of Na₂S₂O₅ and K₂S₂O₈ to give acrylonitrile-[2-(methacryloyloxy)ethyl]dimethyl(3-sulfopropyl)ammonium hydroxide inner salt copolymer (III) [33503-29-6] at 90% conversion (K-value 83.7). III

CRN 140-88-5
CMF C5 H8 O2



L13 ANSWER 60 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1986:452114 CAPLUS

DN 105:52114

TI Polymeric coupler lattices for use in color photographic silver halide elements

AU Monbaliu, Marcel; Dierckx, Jozef; Van de Sande, Christian

CS Agfa-Gevaert N. V., Neth.

SO Res. Discl. (1986), 265, 248-50

CODEN: RSDSBB; ISSN: 0374-4353

DT Journal

LA English

AB A polymeric coupler lattice which can be used in .gtoreq.1 Ag halide emulsion layer or other hydrophilic colloid layer of a photog. element has a recurring unit derived from a monomer QR where Q is a phenol or naphthol moiety capable of forming a yellow dye, a pyrazolone or indazolone coupler moiety forming a magenta dye, a pyrazolone coupler moiety forming a colorless compd., and R = NHCONH(CH₂)₂OCOC(CH₃):CH₂. Thus, a suspension contg. H₂O 360 mL, I 32 g, and 10% aq. Na oleylmethyltauride 24 mL was heated to 90.degree., mixed with 10 mL 1% aq. Na 4,4-dicyano-4,4'-azopentanoic acid, heated at 90.degree. for 5 min, mixed with Bu acrylate 48 g, 1% aq. Na 4,4-dicyano-4,4'-azopentanoic acid and refluxed 30 min to give 430 g of the latex having a polymer content of 16.6 g/100 g of latex and an av. particle size of 51 nm.

IT **103134-50-5P**

RL: PREP (Preparation)

(prepn. of, for color photog. materials)

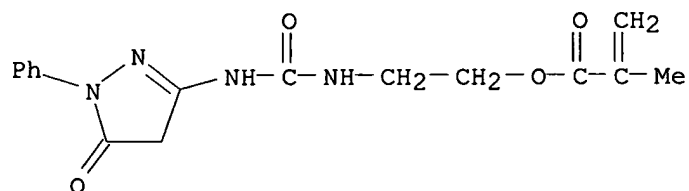
RN 103134-50-5 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(4,5-dihydro-5-oxo-1-phenyl-1H-pyrazol-3-yl)amino]carbonyl]amino]ethyl ester, polymer with butyl 2-propenoate (9CI)
(CA INDEX NAME)

CM 1

CRN 103134-49-2

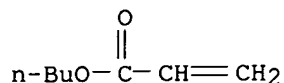
CMF C16 H18 N4 O4



CM 2

CRN 141-32-2

CMF C7 H12 O2



L13 ANSWER 61 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1986:216527 CAPLUS

DN 104:216527

TI Polymeric pyridinium ylide and its products

IN Taylor, Lloyd D.; Haubs, Michael Karl Josef

PA Polaroid Corp. , USA

SO Eur. Pat. Appl., 44 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 164100	A2	19851211	EP 1985-106888	19850605
	EP 164100	A3	19870805		
	EP 164100	B1	19930414		
	R: BE, DE, FR, GB, IT, SE				
	US 4617253	A	19861014	US 1984-617726	19840606
	AU 8543309	A1	19851212	AU 1985-43309	19850605
	AU 570116	B2	19880303		
	JP 61009410	A2	19860117	JP 1985-122354	19850605
	JP 05048270	B4	19930721		
	CA 1258653	A1	19890822	CA 1985-483186	19850605
	US 4670528	A	19870602	US 1986-879394	19860627
	AU 8810290	A1	19880428	AU 1988-10290	19880114
	AU 591373	B2	19891130		
	CA 1260649	A2	19890926	CA 1989-591570	19890220
PRAI	US 1984-617726		19840606		
	CA 1985-483186		19850605		

OS CASREACT 104:216527

AB Pyridinium ylide-contg. polymers are exposed to actinic radiation to produce water-insol. or hydrophobic N-acyldiazepine polymers for the prodn. of printing plates, photoresists, and printed circuit boards as well as the waterproofing or hydrophobization of surfaces. Thus, N-(2-hydroxypropyl)methacrylamide was reacted with N,N'-carbonyldiimidazole and the resulting amido compd. reacted with 1-aminopyridinium chloride in the presence of K₂CO₃ to give I, dissolved in H₂O, azobis(4-cyanopentanoic acid) added, and heated to 70.degree. in the absence of O to give a I homopolymer. A 3% aq. soln. of the I homopolymer was spin-coated on a Si wafer, exposed to a UV lamp through a photomask and developed in a H₂O bath to give an image showing good resolu. of lines of 2.5 .mu. spacing. The adhesion of the polymeric image to the water surface was also found to be excellent.

IT 102223-94-9 102223-97-2

RL: USES (Uses)

(photosensitive compns. contg., for prodn. of hydrophobic patterns)

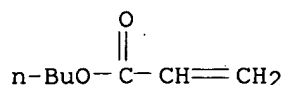
RN 102223-94-9 CAPLUS

CN Pyridinium, 1-[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]carbonyl]amino]-, inner salt, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 102223-93-8

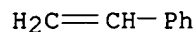
CMF C12 H15 N3 O3



CM 3

CRN 100-42-5

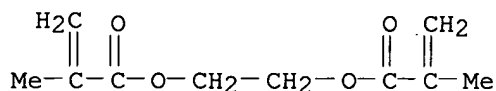
CMF C8 H8



CM 4

CRN 97-90-5

CMF C10 H14 O4



L13 ANSWER 56 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1987:600537 CAPLUS

DN 107:200537

TI Stable dispersion coating compositions

IN Miyazono, Tadafumi; Kashiwara, Akio; Ishikura, Shinichi

PA Nippon Paint Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 8 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 62167366	A2	19870723	JP 1986-8444	19860117
	JP 06096692	B4	19941130		

AB The title compns. contain binders, liq. media, crosslinked, insol. resin particles (av. diam. 0.01-10 .mu.), and compd. contg. groups with mol. cohesive energy >6500 cal/mol. A dispersion of 20 parts 30:35:35 Bu acrylate-ethylene glycol dimethacrylate-styrene copolymer particles (av. diam. 90 m.mu.) in 10 parts MeOCH₂CH₂OH and 70 parts xylene was mixed with a 50% polymer soln. (from styrene 300, 2-ethylhexyl methacrylate 400, 2-ethylhexyl acrylate 107, 2-hydroxyethyl methacrylate 162, and methacrylic acid 31 parts) 280, U-Van 20SE-60 120, and ethanolamine-hexamethylene diisocyanate adduct 20 parts were mixed and thinned with xylene to Ford Cup No. 4 viscosity 25 s to give a compn. stable for >1 wk at 20.degree..

IT 110782-99-5

RL: TEM (Technical or engineered material use); USES (Uses)
(coatings, high-solids, storage-stable)

RN 110782-99-5 CAPLUS

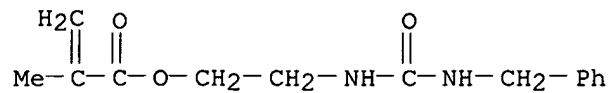
CN 2-Propenoic acid, 2-methyl-, polymer with ethenylbenzene, 2-ethylhexyl 2-methyl-2-propenoate, 2-ethylhexyl 2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate and 2-[[[(phenylmethyl)amino]carbonyl]amino]ethyl

2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 110782-91-7

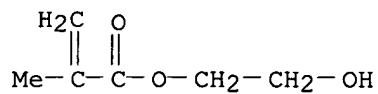
CMF C14 H18 N2 O3



CM 2

CRN 868-77-9

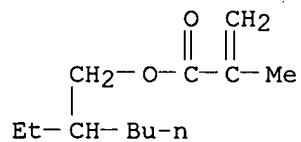
CMF C6 H10 O3



CM 3

CRN 688-84-6

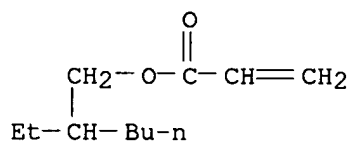
CMF C12 H22 O2



CM 4

CRN 103-11-7

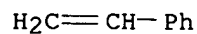
CMF C11 H20 O2



CM 5

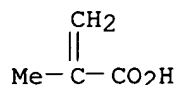
CRN 100-42-5

CMF C8 H8



CM 6

CRN 79-41-4
CMF C4 H6 O2



L13 ANSWER 57 OF 69 CAPLUS COPYRIGHT 2002 ACS
AN 1987:578254 CAPLUS
DN 107:178254
TI High-solids coating compositions
IN Miyazono, Tadafumi; Kashiwara, Akio; Ishikura, Shinichi
PA Nippon Paint Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 62167367	A2	19870723	JP 1986-8445	19860117
	JP 06096693	B4	19941130		
	CA 1293579	A1	19911224	CA 1987-527556	19870116
	EP 238166	A2	19870923	EP 1987-300438	19870119
	EP 238166	A3	19880720		
	EP 238166	B1	19910918		
	EP 238166	B2	19940921		

R: DE, FR, GB

PRAI JP 1986-8443 19860117
JP 1986-8445 19860117

AB The title compns. having excellent workability and storability and providing high-gloss smooth-surfaced coatings contain (A) film-forming polymer, (B) volatile org. thinner in which the above polymer is dissolved or dispersed, and (C) 3-dimensional resin particles (av. diam. 0.01-10 .mu.) contg. -NHY- group (Y = CONH, CO2, CO). A dispersion of 20 parts 90 m.mu.-diam. 3-dimensional resin particles (from styrene 35, ethylene glycol dimethacrylate 35, Bu acrylate 26, and PhCH2NHCONHCH2CH2O2CCMe:CH2 4 parts) in xylene 42, MIBK 30, and BuOH 8 parts was mixed with 280 parts 50%-solids varnish (from styrene 300, 2-ethylhexyl methacrylate 400, 2-ethylhexyl acrylate 107, 2-hydroxyethyl methacrylate 162, and methacrylic acid 31 parts in xylene) and 120 parts U-Van 20 SE-60, thinned with xylene to Ford Cup No. 4 viscosity 25 s, spray-coated 40 .mu. thick on a vertical tinplate, set 5 min, and baked at 140.degree. for 25 min.

IT 110782-99-5

RL: TEM (Technical or engineered material use); USES (Uses)
(coatings, contg. crosslinked acrylic polymer particles, high-solids)

RN 110782-99-5 CAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with ethenylbenzene, 2-ethylhexyl 2-methyl-2-propenoate, 2-ethylhexyl 2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate and 2-[[[(phenylmethyl)amino]carbonyl]amino]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 110782-91-7
CMF C14 H18 N2 O3

L13 ANSWER 51 OF 69 CAPLUS COPYRIGHT 2002 ACS

AN 1989:202728 CAPLUS

DN 110:202728

TI Magenta coupler monomer, polymeric magenta coupler and recording material for color photography therefrom

IN Helling, Guenter

PA Agfa-Gevaert A.-G., Fed. Rep. Ger.

SO Eur. Pat. Appl., 18 pp.

CODEN: EPXXDW

DT Patent

LA German

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 294681	A2	19881214	EP 1988-108645	19880531
	EP 294681	A3	19910306		
	EP 294681	B1	19940302		

R: BE, DE, FR, GB

	DE 3722497	A1	19881229	DE 1987-3722497	19870708
	US 4921782	A	19900501	US 1988-200541	19880531
	JP 64002046	A2	19890106	JP 1988-135766	19880603
PRAI	DE 1987-3719401		19870611		
	DE 1987-3722497		19870708		

OS CASREACT 110:202728

AB Polymeric magenta couplers giving magenta dye images with a high Dmax are prep'd. by using a polymerizable unit from a carboxyl group-contg. polymerizable pyrazoloazole coupler of the formula I (R1 = H, alkyl, aralkyl, or aryl; X = H or a group releaseable upon coupling; Za, Zb, or Zc = an optionally substituted methine, N, or NH group; .gtoreq.1 of R1 and X or a substituent on Za, Zb, or Zc contains ethylenically unsatd. group; and .gtoreq.1 of R1 and X or a substituent on Za, zb, or Zc contains a CO2H group). A typical magenta coupler, obtained by polymn. of Et acrylate and II, was used in a color photog. material to produce a magenta image with a high Dmax.

IT **120398-17-6P 120398-24-5P 120416-19-5P**

RL: PREP (Preparation)

(prepn. and photog. coupler applications of)

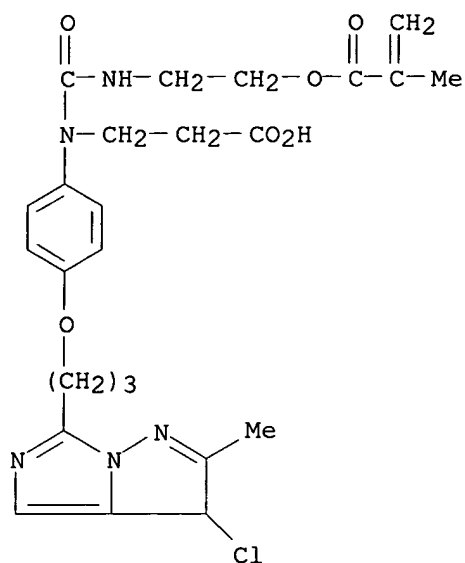
RN 120398-17-6 CAPLUS

CN .beta.-Alanine, N-[4-[3-(3-chloro-2-methyl-3H-imidazo[1,5-b]pyrazol-6-yl)propoxy]phenyl]-N-[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]carbonyl]-, polymer with butyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 120397-80-0

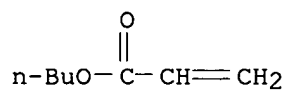
CMF C25 H30 Cl N5 O6



CM 2

CRN 141-32-2

CMF C7 H12 O2



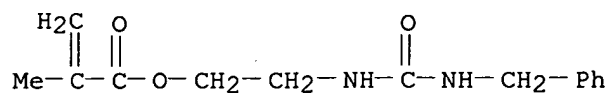
RN 120398-24-5 CAPLUS

CN .beta.-Alanine, N-[4-[3-(3-chloro-2-methyl-3H-imidazo[1,5-b]pyrazol-6-yl)propoxy]phenyl]-N-[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]carbonyl]-, polymer with butyl 2-propenoate and N-(1-methylethyl)-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 120397-80-0

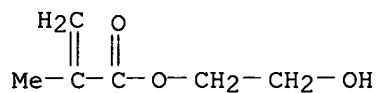
CMF C25 H30 Cl N5 O6



CM 2

CRN 868-77-9

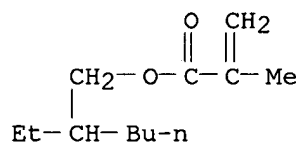
CMF C6 H10 O3



CM 3

CRN 688-84-6

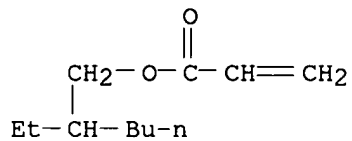
CMF C12 H22 O2



CM 4

CRN 103-11-7

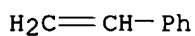
CMF C11 H20 O2



CM 5

CRN 100-42-5

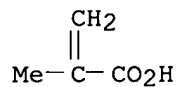
CMF C8 H8



CM 6

CRN 79-41-4

CMF C4 H6 O2



IT 110782-92-8

RL: USES (Uses)

(crosslinked particles, in high-solids acrylic coatings)

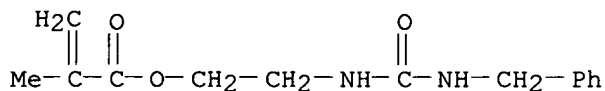
RN 110782-92-8 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1,2-ethanediyl ester, polymer with butyl 2-propenoate, ethenylbenzene and 2-[[[(phenylmethyl)amino]carbonyl]amino]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 110782-91-7

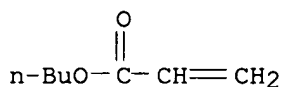
CMF C14 H18 N2 O3



CM 2

CRN 141-32-2

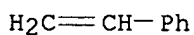
CMF C7 H12 O2



CM 3

CRN 100-42-5

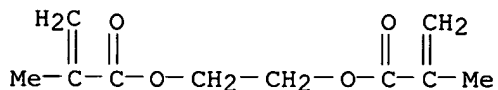
CMF C8 H8



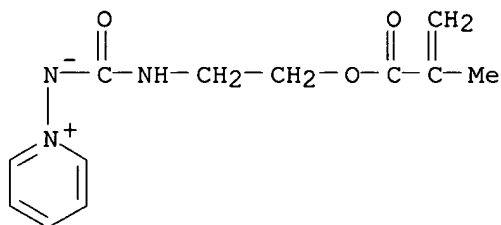
CM 4

CRN 97-90-5

CMF C10 H14 O4

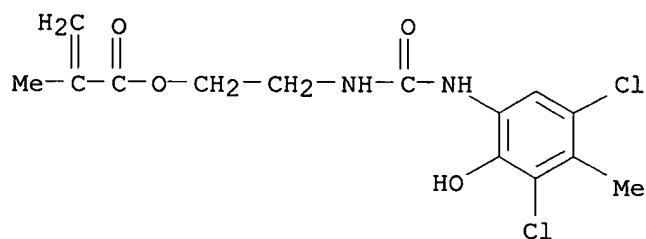


AN 1987:524300 CAPLUS
 DN 107:124300
 TI Photosensitive monolayers, bilayer membranes and polymers
 AU Haubs, M.; Ringsdorf, H.
 CS Inst. Org. Chem., Univ. Mainz, Mainz, 6500, Fed. Rep. Ger.
 SO New J. Chem. (1987), 11(2), 151-6
 CODEN: NJCHE5
 DT Journal
 LA English
 AB Photochem. variation of monolayers and liposomes using the photoisomerization of 1-iminopyridinium ylides, the photocleavage of benzylammonium salts and the photopolymerization of diacetylenes and butadienes is discussed. Photoisomerization of 1-iminopyridinium ylides was applied to a polymeric systems and is discussed with respect to the photochem. variation of polymer properties.
 IT **102223-94-9 110161-79-0**
 RL: USES (Uses)
 (photolysis of films of, for photoresist applications)
 RN 102223-94-9 CAPLUS
 CN Pyridinium, 1-[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]carbonyl]amino]-, inner salt, homopolymer (9CI) (CA INDEX NAME)
 CM 1
 CRN 102223-93-8
 CMF C12 H15 N3 O3

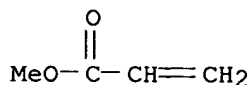


L13 ANSWER 59 OF 69 CAPLUS COPYRIGHT 2002 ACS
 AN 1986:562153 CAPLUS
 DN 105:162153
 TI Silver halide color photographic photosensitive materials
 IN Matsunaga, Satoshi; Sasaki, Takashi; Yoshimoto, Shinji; Mizukura, Noboru;
 Ueda, Eiichi
 PA Konishiroku Photo Industry Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 22 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 61035444	A2	19860219	JP 1984-158337	19840728
AB	The title materials contain (co)polymer cyan coupler having structural repeating units from monomers of the formula I (R = H, halo; R1 = H, alkyl; R2 = H, a group released during coupling reaction; R3 = ethylenically unsatd. group; Z = NHCO2, NHCONH; Z1 = org. divalent moiety). The cyan couplers give dye images with excellent light and heat fastness without causing yellow stains. Thus, color photog. paper prepd. by using a cyan coupler obtained by copolymn. of Me acrylate, methacrylic acid and II showed high optical d. and low fog.				
IT	104490-95-1 104490-97-3 104493-67-6 104493-68-7				
	RL: TEM (Technical or engineered material use); USES (Uses) (photog. cyan coupler)				
RN	104490-95-1 CAPLUS				
CN	2-Propenoic acid, 2-methyl-, 2-[[[(3,5-dichloro-2-hydroxy-4-methylphenyl)amino]carbonyl]amino]ethyl ester, polymer with methyl 2-propenoate and 2-propenoic acid (9CI) (CA INDEX NAME)				
CM	1				
CRN	103230-09-7				
CMF	C14 H16 Cl2 N2 O4				

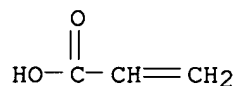


CM 2
 CRN 96-33-3
 CMF C4 H6 O2



CM 3

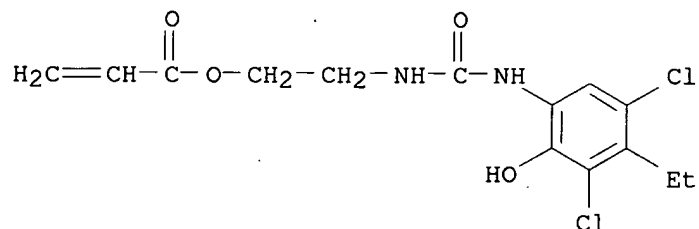
CRN 79-10-7
CMF C3 H4 O2



RN 104490-97-3 CAPLUS
CN 2-Propenoic acid, 2-[[[(3,5-dichloro-4-ethyl-2-hydroxyphenyl)amino]carbonyl]amino]ethyl ester, polymer with ethyl 2-propenoate and 2-propenamide (9CI) (CA INDEX NAME)

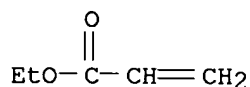
CM 1

CRN 104490-96-2
CMF C14 H16 Cl2 N2 O4



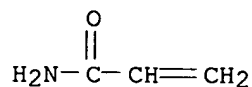
CM 2

CRN 140-88-5
CMF C5 H8 O2



CM 3

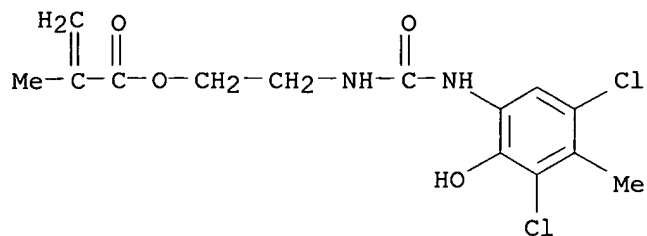
CRN 79-06-1
CMF C3 H5 N O



RN 104493-67-6 CAPLUS
CN 2-Propenoic acid, 2-methyl-, polymer with 2-[[[(3,5-dichloro-2-hydroxy-4-methylphenyl)amino]carbonyl]amino]ethyl 2-methyl-2-propenoate and methyl 2-propenoate (9CI) (CA INDEX NAME)

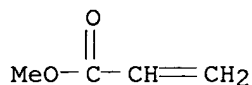
CM 1

CRN 103230-09-7
CMF C14 H16 Cl2 N2 O4



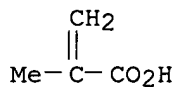
CM 2

CRN 96-33-3
CMF C4 H6 O2



CM 3

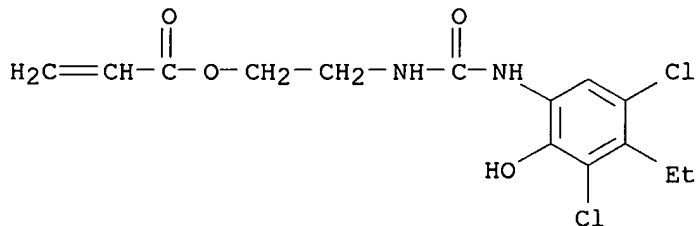
CRN 79-41-4
CMF C4 H6 O2



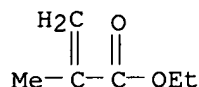
RN 104493-68-7 CAPLUS
CN 2-Propenoic acid, 2-[[[(3,5-dichloro-4-ethyl-2-hydroxyphenyl)amino]carbonyl]amino]ethyl ester, polymer with ethyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 104490-96-2
CMF C14 H16 Cl2 N2 O4



CM 2



L29 ANSWER 15 OF 17 CAPLUS COPYRIGHT 2002 ACS

AN 1992:449992 CAPLUS

DN 117:49992

TI Thioxanthone compounds and **photosensitive** compositions containing them

IN Ohayashi, Hiroharu; Minami, Toru; Noda, Mariko; Hasegawa, Kenichi

PA Sanyo Chemical Industries, Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 8 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 04026687	A2	19920129	JP 1990-132788	19900523
OS	MARPAT 117:49992				

AB The title compns., useful for printing plates, coatings, adhesives, etc., contain unsatd. thioxanthenes I (R = H, Me; A = C1-7 alkylene; Y, Y' = C1-6 alkyl, alkoxy, alkylthio, halo, nitro, amino, C1-6 alkylamino, hydroxyalkylamino, alkanoylamino, sulfonamido, Ac; n = 1-4; m, q = 0-3). Thus, treating 2.5 g 2-hydroxythioxanthone with 1.8 g 2-isocyanatoethyl methacrylate in AcNMe₂ in presence of dibutyltin dilaurate gave 2.8 g unsatd. urethane, which was blended with PMMA, Et diethylaminobenzoate, Kayaset Blue 136, and CH₂Cl₂, then applied on an Al sheet and dried to give a **photosensitive** sheet with high sensitivity and good storage stability.

IT **142416-98-6P 142416-99-7P 142417-00-3P**

RL: PREP (Preparation)
(prepn. of)

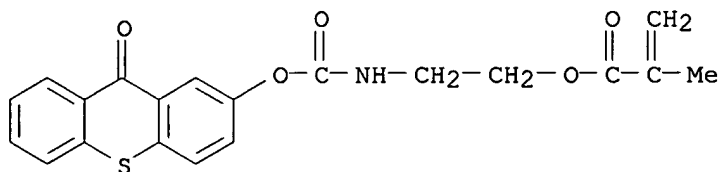
RN 142416-98-6 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(9-oxo-9H-thioxanthen-7-yl)oxy]carbonyl]amino]ethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 142415-27-8

CMF C20 H17 N O5 S



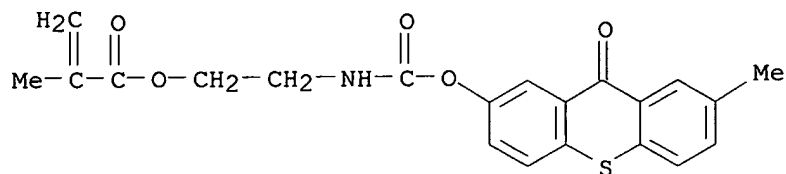
RN 142416-99-7 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(2-methyl-9-oxo-9H-thioxanthen-7-yl)oxy]carbonyl]amino]ethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 142415-28-9

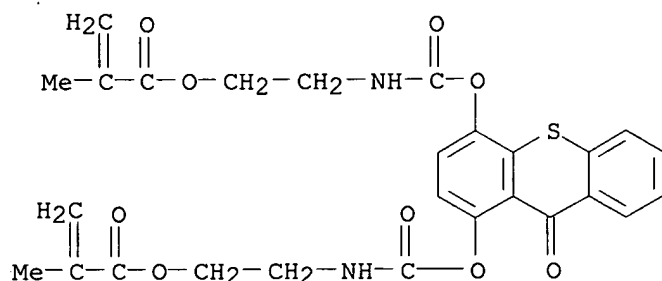
CMF C21 H19 N O5 S



RN 142417-00-3 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, (9-oxo-9H-thioxanthene-5,8-diyl)bis(oxy-carbonylimino-2,1-ethanediyl) ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 142415-29-0
 CMF C27 H26 N2 O9 S



L29 ANSWER 16 OF 17 CAPLUS COPYRIGHT 2002 ACS
 AN 1990:515343 CAPLUS
 DN 113:115343
 TI Halomethyl-1,3,5-triazines containing a monomeric moiety
 IN Bonham, James A.; Rossman, Mitchell A.; Grant, Richard J.
 PA Minnesota Mining and Mfg. Co., USA
 SO Eur. Pat. Appl., 21 pp.
 CODEN: EPXXDW
 DT Patent
 LA English
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 359430	A2	19900321	EP 1989-308688	19890829
	EP 359430	A3	19900411		
	EP 359430	B1	19950510		
	R: BE, DE, FR, GB, IT, NL				
	JP 02149570	A2	19900608	JP 1989-231344	19890906
	JP 2825547	B2	19981118		
	KR 9705533	B1	19970417	KR 1989-12839	19890906
	US 5387682	A	19950207	US 1993-49555	19930419
	US 5496504	A	19960305	US 1994-345594	19941128
PRAI	US 1988-241691	A	19880907		
	US 1990-555301	B1	19900718		
	US 1993-49555	A3	19930419		

OS MARPAT 113:115343

AB The title compns. [I; A = mono-, di- and trihalomethyl; M = polymerizable monomeric moiety capable of undergoing free radical or ionic chain

polymn., e.g. acrylate, methacrylate, acrylamide, vinyl ether, allyl ether, epoxide, and allyl amine group; L = covalent bond or group; Y = any group of A or LM, NHR, NR2, OR, (un)substituted alkyl, alkenyl, or (hetero)aryl; R = (un)substituted alkyl, aryl], **radiation**-sensitive compds. having a photo-labile halomethyl-1,3,5-triazine moiety and .gtoreq.1 polymerizable moiety within 1 mol., were prepd. I are photoinitiators for printing, duplicating, copying, and other imaging compns. that can be stimulated by actinic **radiation** at wavelengths of .apprx.250-900 nm to generate free radicals, and can be used to prep. 1,3,5-triazine-substituted polymers. PhMe soln. of 0.006 mol 2,4-bis(trichloromethyl)-6-isocyanato-1,3,5-triazine was added to a PhMe soln. of 0.008 mol 2-hydroxyethyl acrylate, 12 drops di-n-butyltin dilaurate, and 100 mg phenothiazine, and the reaction mixt. was stirred 24-72 h at room temp. under N to give I (A = Y = CCl3, LM = NHCO2CH2CH2O2CCH:CH2). A total of 23 I were prepd. One example illustrated the use of I as initiators in light-sensitive coatings.

IT 128930-95-0P

RL: SPN (Synthetic preparation); PREP (Preparation)
(prepn. of)

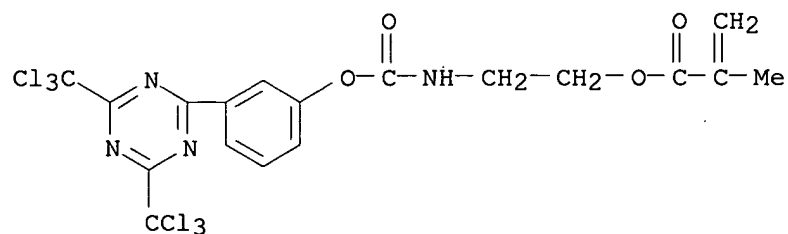
RN 128930-95-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[3-[4,6-bis(trichloromethyl)-1,3,5-triazin-2-yl]phenoxy]carbonyl]amino]ethyl ester, polymer with octyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 128930-94-9

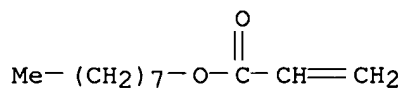
CMF C18 H14 Cl6 N4 O4



CM 2

CRN 2499-59-4

CMF C11 H20 O2



L29 ANSWER 17 OF 17 CAPLUS COPYRIGHT 2002 ACS

AN 1990:488285 CAPLUS

DN 113:88285

TI Lithographic plate blanks for electrophotographic plate making

IN Kato, Eiichi; Ishii, Kazuo

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 30 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 02015277	A2	19900118	JP 1988-17421	19880129
	US 4971871	A	19901120	US 1989-303508	19890130
PRAI	JP 1988-17421		19880129		
	JP 1988-22062		19880203		

AB In the title blank composed of an elec. conductive support and .gtoreq.1 photoconductive layer comprising photoconductive ZnO and a binder, the binder resin contains .gtoreq.1 functional groups capable of yielding upon decompn., a SH, phospho., NH2, and(or) a SO3H group, and incorporates a crosslinking agent.

IT 128635-61-0

RL: USES (Uses)

(photoconductive layer contg., for lithog. plate blanks for electrophotog. plate making)

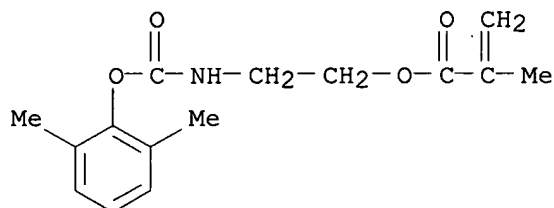
RN 128635-61-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with 1,6-diisocyanatohexane, 2-[[(2,6-dimethylphenoxy) carbonyl] amino] ethyl 2-methyl-2-propenoate and 4-hydroxybutyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 128382-30-9

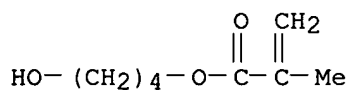
CMF C15 H19 N O4



CM 2

CRN 997-46-6

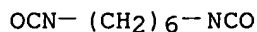
CMF C8 H14 O3



CM 3

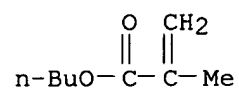
CRN 822-06-0

CMF C8 H12 N2 O2



CM 4

CRN 97-88-1
CMF C8 H14 O2



=>

(FILE 'HOME' ENTERED AT 12:40:16 ON 02 JUL 2002)

FILE 'REGISTRY' ENTERED AT 12:40:29 ON 02 JUL 2002

L1 SCREEN 970 AND 1015 AND 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 0 S L3 FULL
L5 SCREEN 970 AND 2067
L6 STRUCTURE UPLOADED
L7 QUE L6 AND L5
L8 97 S L7 FULL
L9 SCREEN 970 AND 2067
L10 STRUCTURE UPLOADED
L11 QUE L10 AND L9
L12 0 S L11 FULL

FILE 'CAPLUS' ENTERED AT 12:52:00 ON 02 JUL 2002

L13 69 S L8

FILE 'REGISTRY' ENTERED AT 13:15:38 ON 02 JUL 2002

L14 SCREEN 970 AND 2067
L15 STRUCTURE UPLOADED
L16 QUE L15 AND L14
L17 0 S L16 FULL
L18 SCREEN 970 AND 2067
L19 STRUCTURE UPLOADED
L20 QUE L19 AND L18
L21 121 S L20 FULL

FILE 'CAPLUS' ENTERED AT 13:19:48 ON 02 JUL 2002

L22 74 S L21

FILE 'REGISTRY' ENTERED AT 13:24:46 ON 02 JUL 2002

L23 SCREEN 970 AND 2067
L24 STRUCTURE UPLOADED
L25 QUE L24 AND L23
L26 129 S L25 FULL

FILE 'CAPLUS' ENTERED AT 13:25:21 ON 02 JUL 2002

L27 90 S L26
L28 619981 S ANTIREFLECTIVE OR RADIATION OR PHOTSENSITIVE
L29 17 S L27 AND L28